

Technical meeting on emerging applications of plasma science and technology

ML-aided plasma source and process simulation for semiconductor fabrication processes

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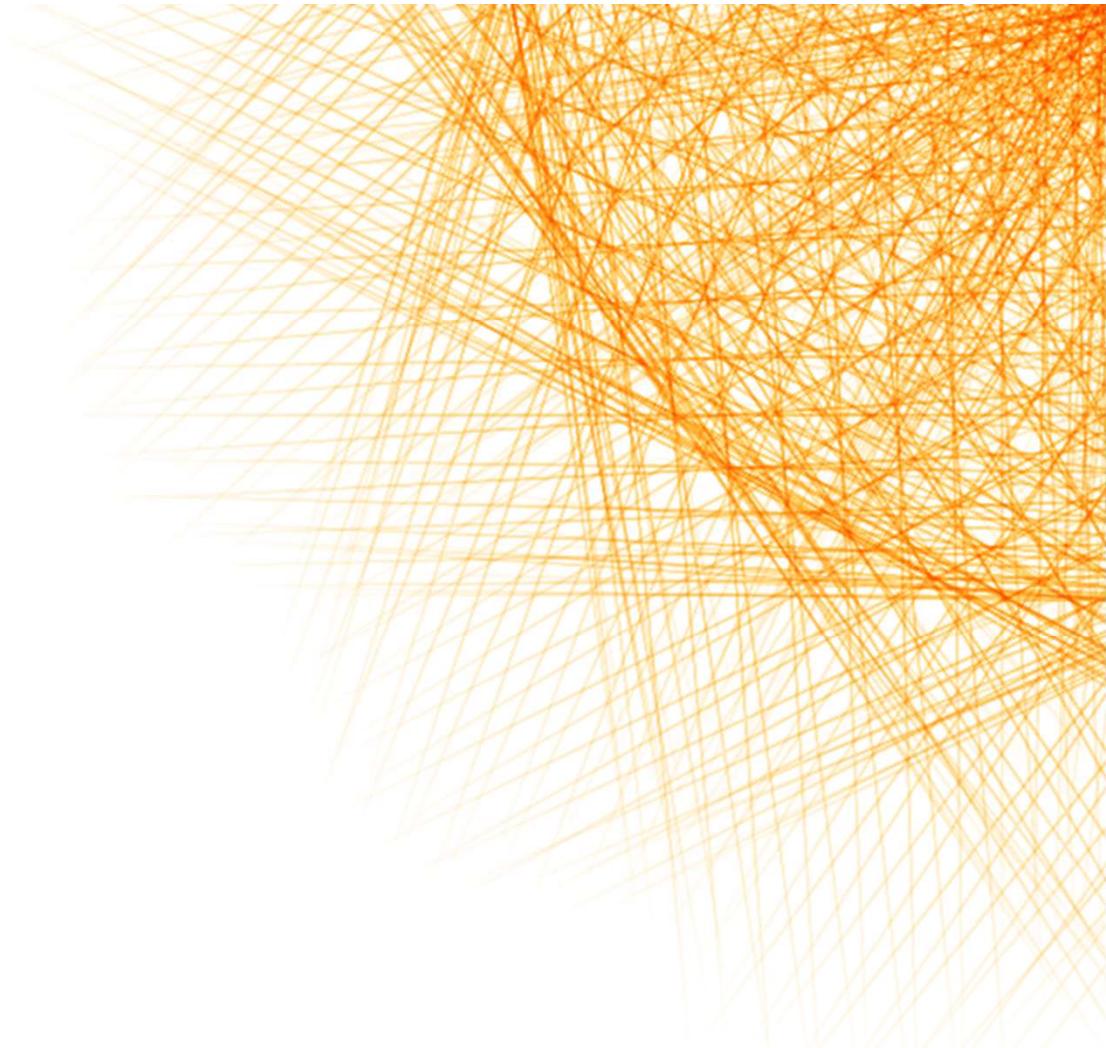
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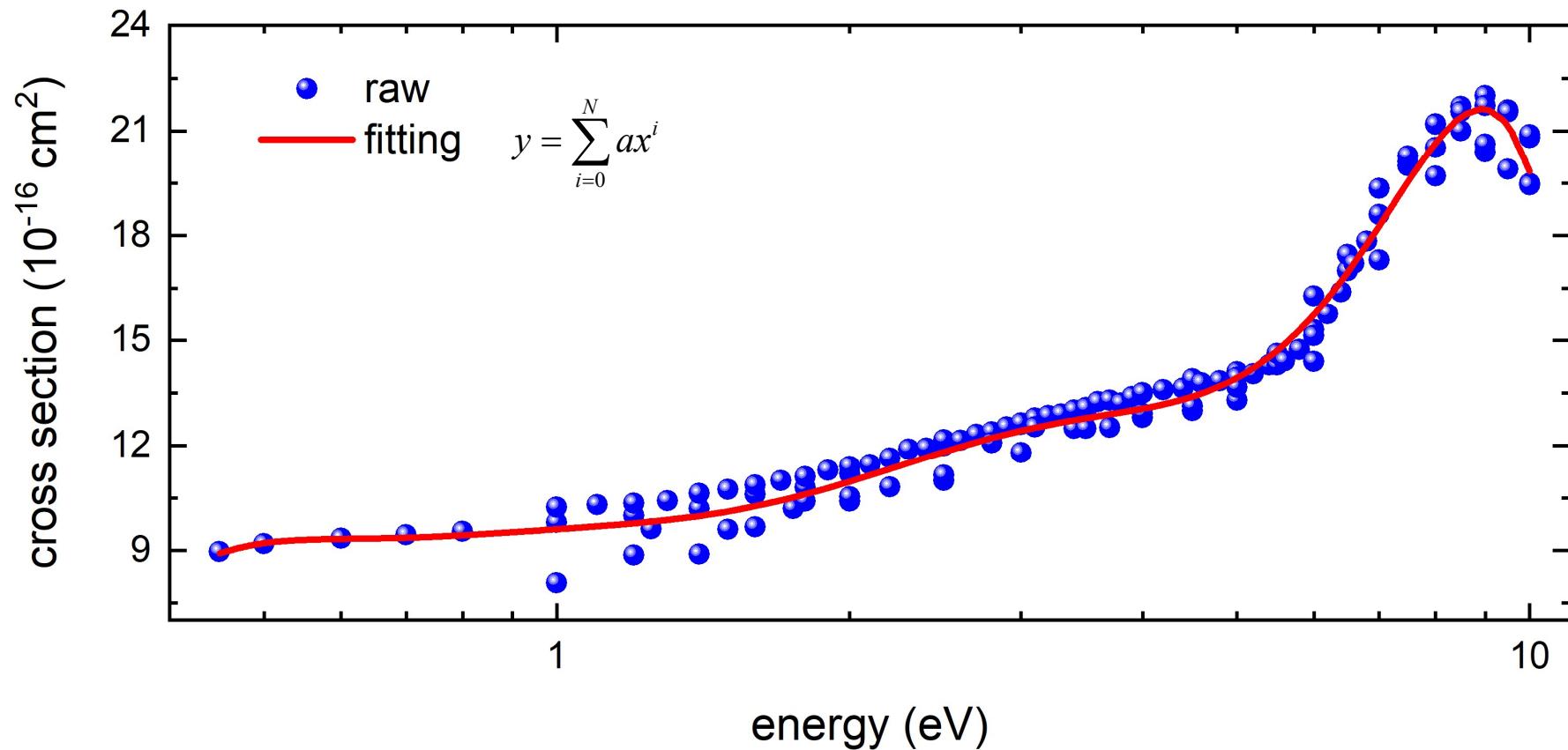
1

Introduction



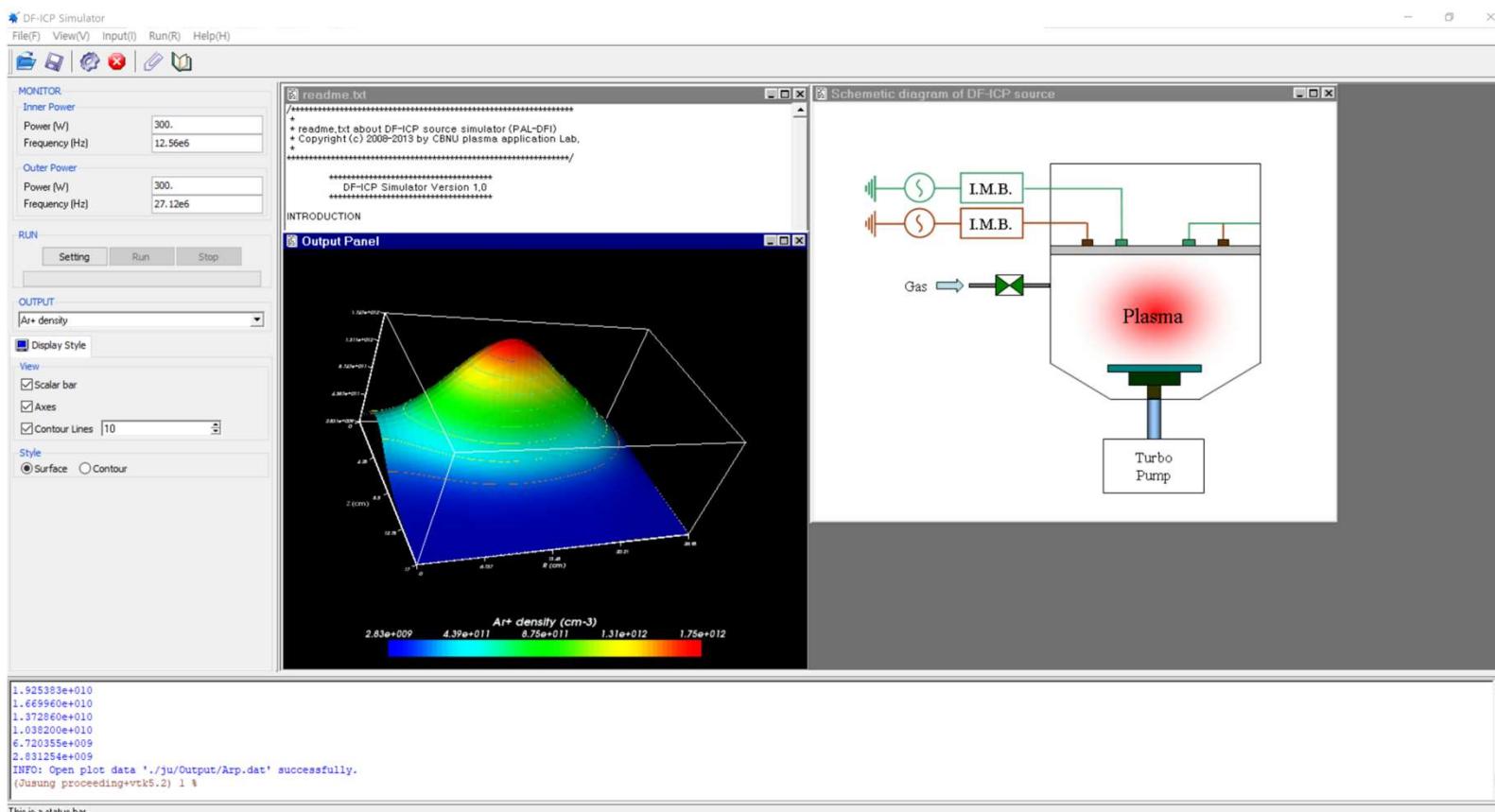
1. Introduction

Motivation & Need for development



1. Introduction

Motivation & Need for development

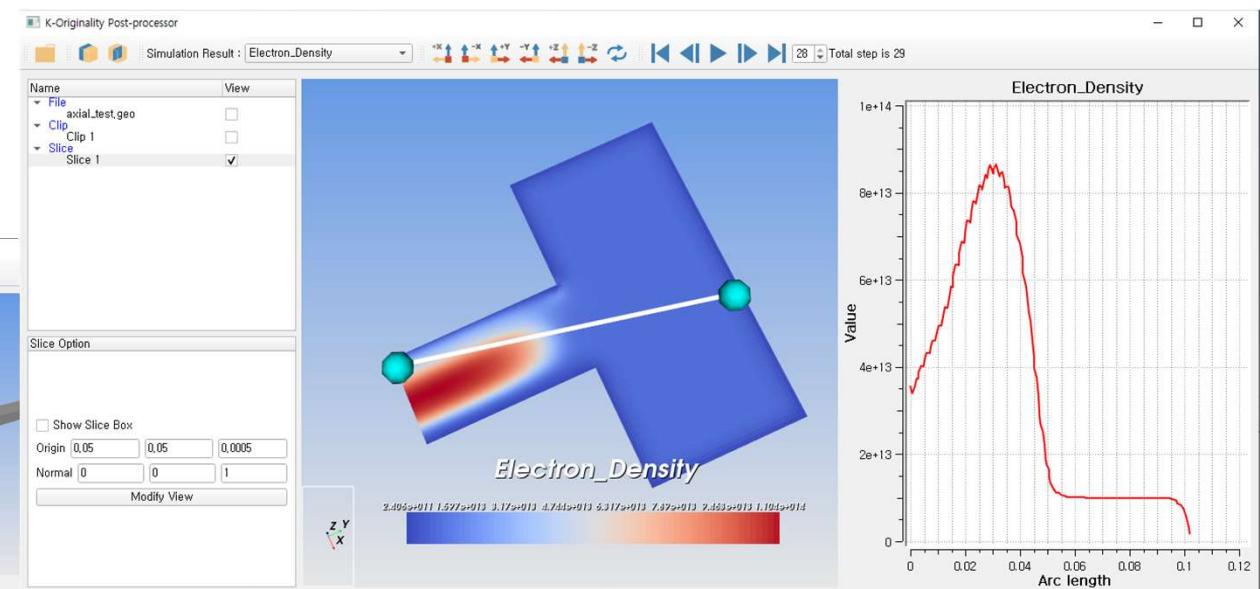
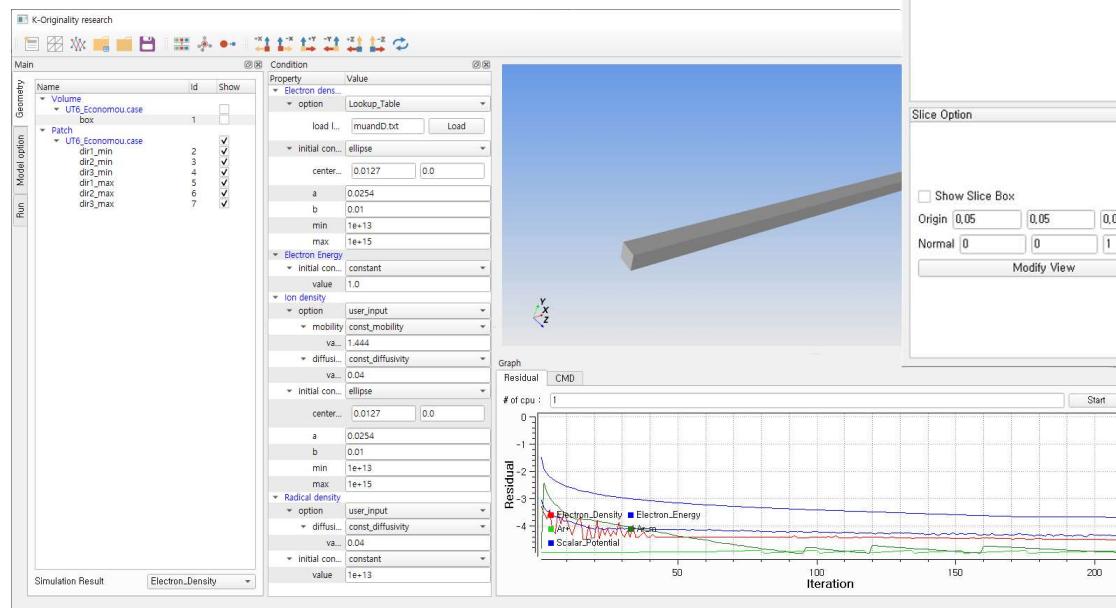


- Language : C, Tcl/TK, VTK
- Source : TCP/ICP
- Model :
 - Fluid model
 - Non-local heating model
 - Cylindrical 2D geometry
 - Ar plasma

1. Introduction

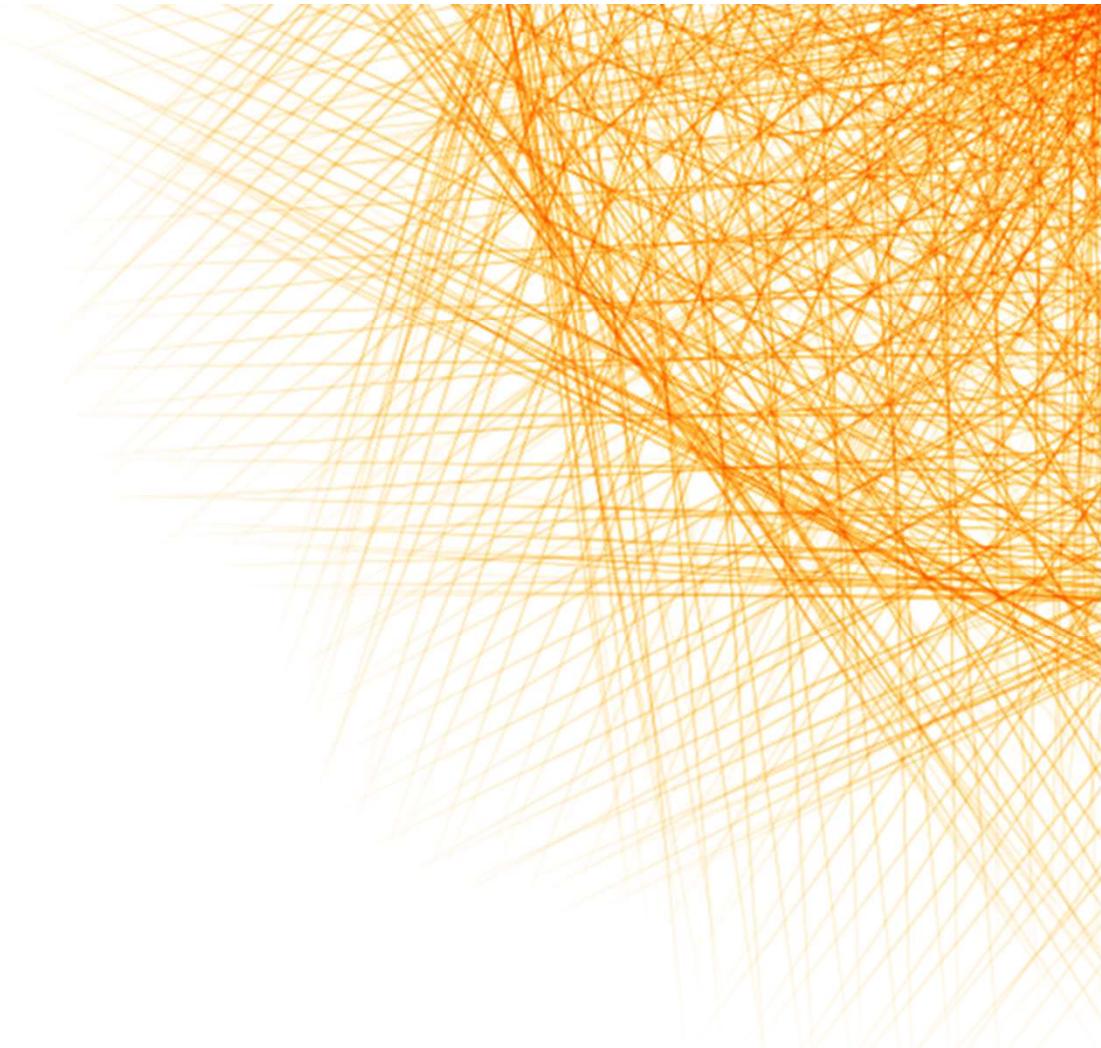
Developed 3D simulator

- Fluid equation + Boltzmann equation
- 3D Polyhedral mesh
- Finite volume method
- C++, VTK
- Bulk and surface DB



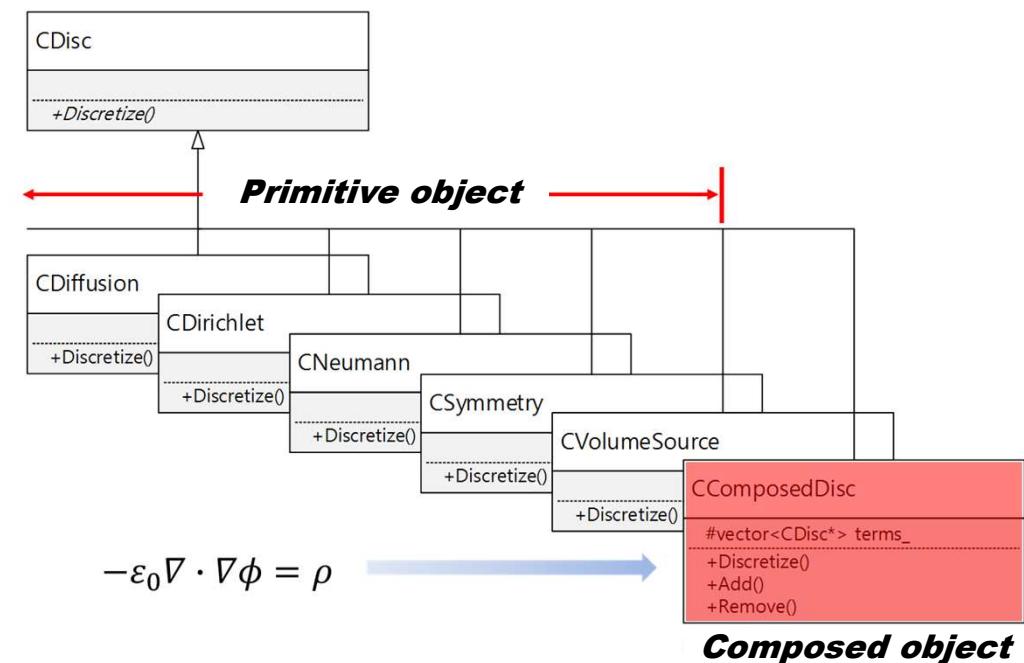
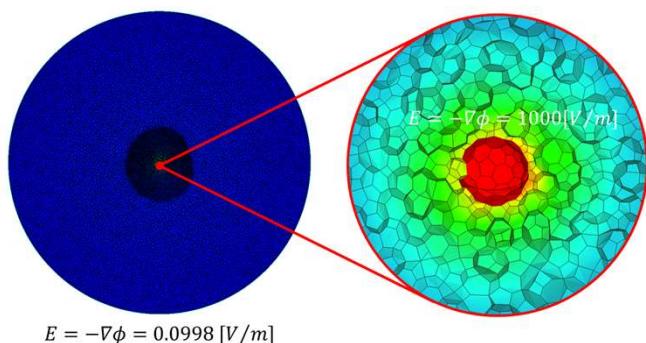
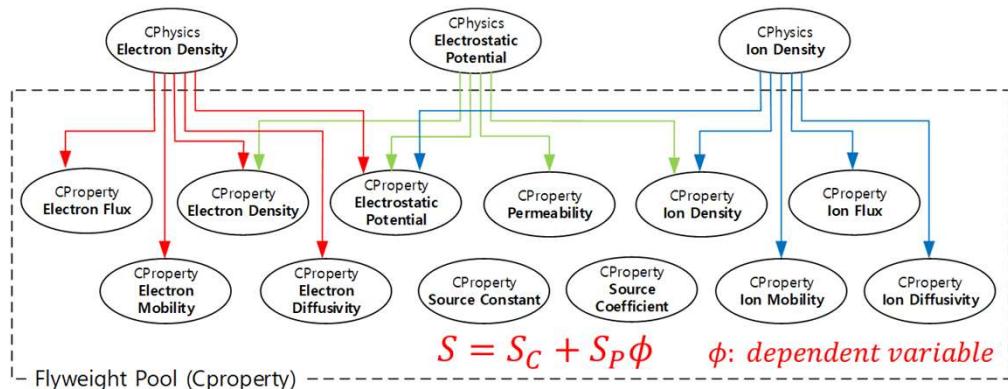
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Plasma Modeling



2. Plasma Modeling

Flyweight pool and composite pattern

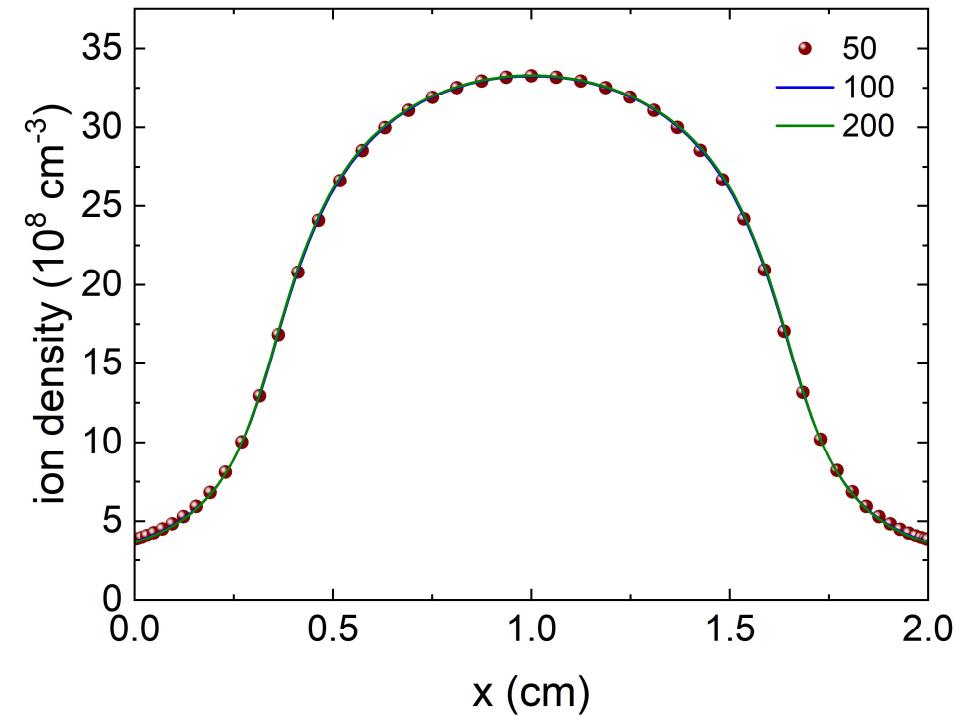
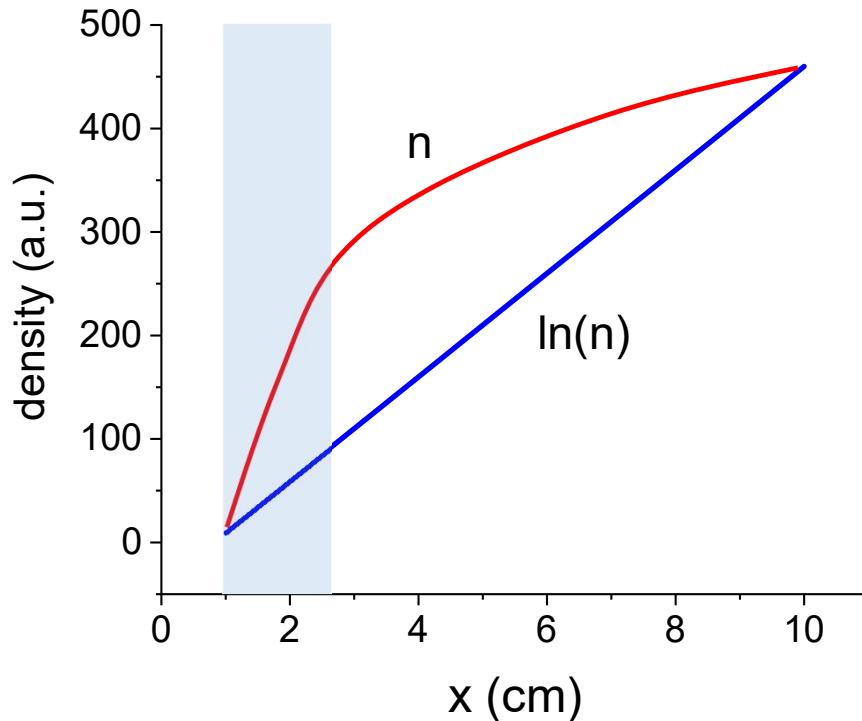


2. Plasma Modeling

Log transformation

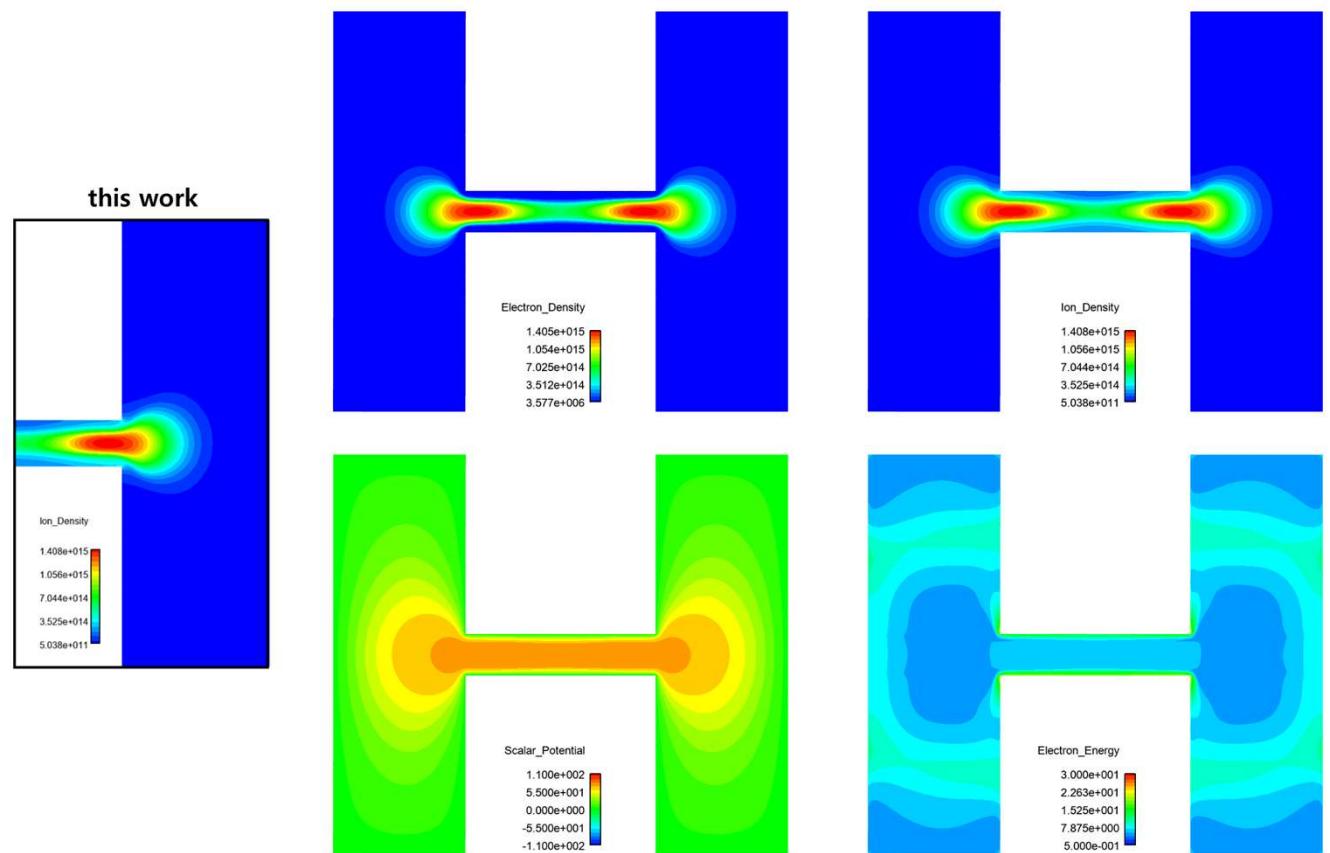
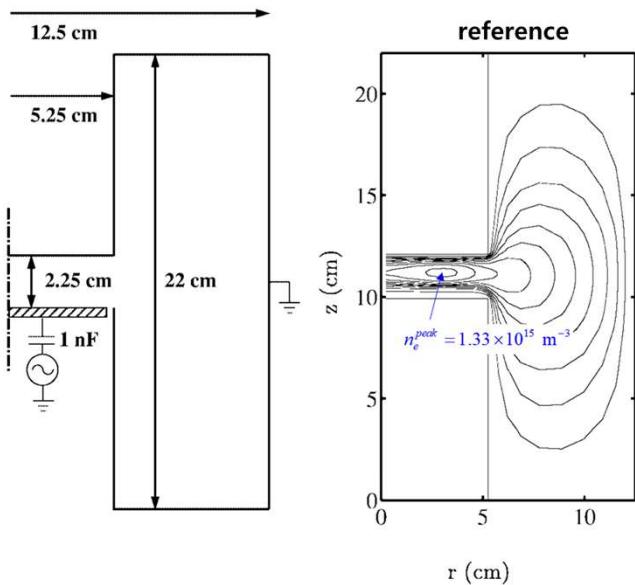
- Improves linearity between independent and dependent variables
- CCP 1D discharge → reduce grid dependence of results

$$\frac{\partial n_e}{\partial t} = \frac{n_e}{n_e} \frac{\partial n_e}{\partial t} = n_e \frac{\partial (\ln n_e)}{\partial t} = n_e \frac{\partial N_e}{\partial t}$$



2. Plasma Modeling

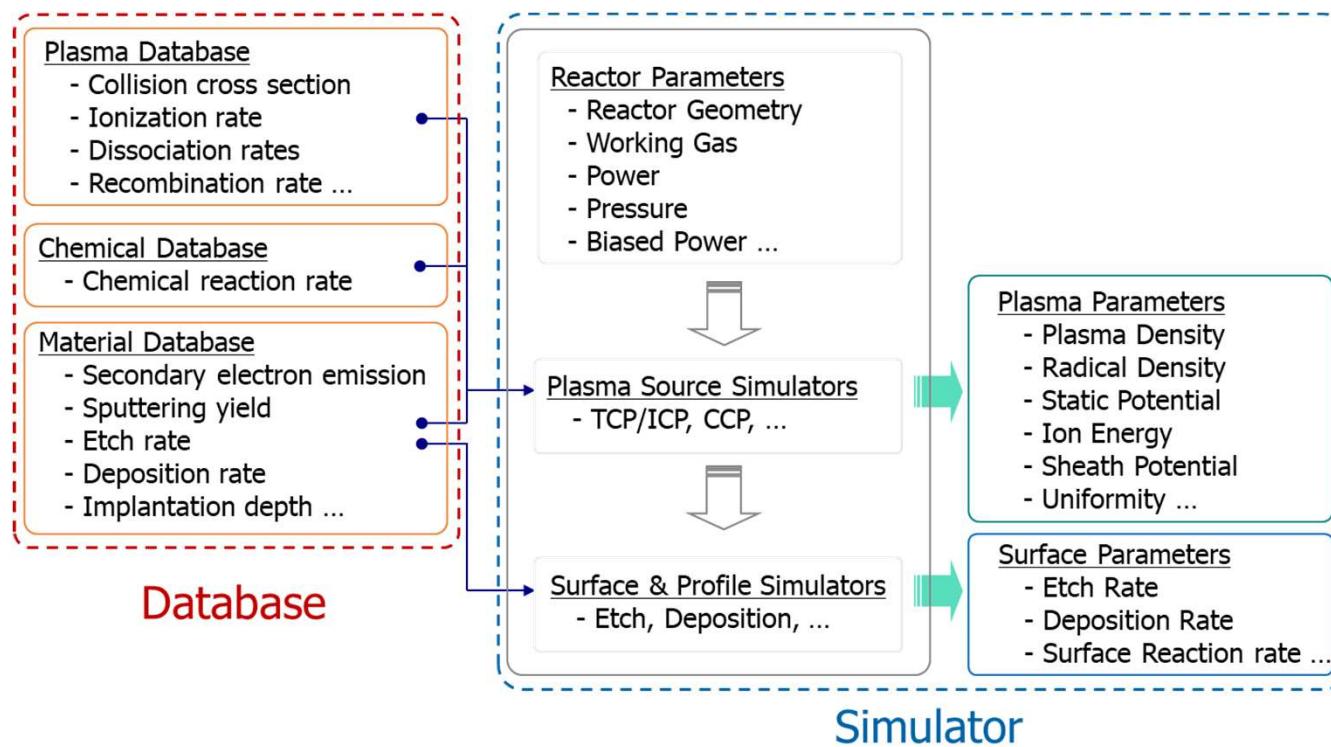
K-PLASMA unit test



2. Plasma Modeling

Database development

- Bulk and surface chemistry data base (DB) are necessarily required to compute the plasma parameters.
- High reliable DB is closely related with accuracy enhancement of simulations.



2. Plasma Modeling

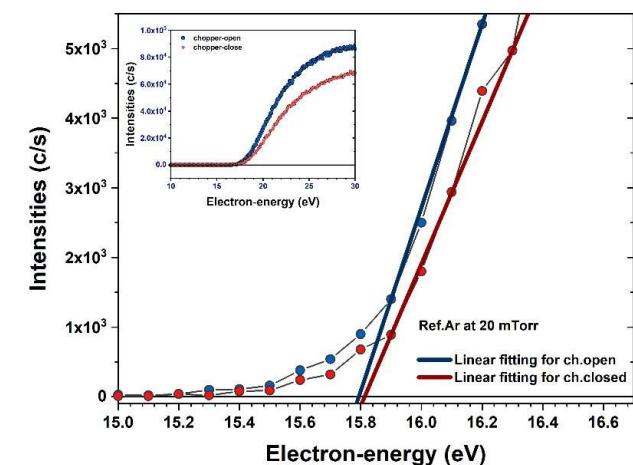
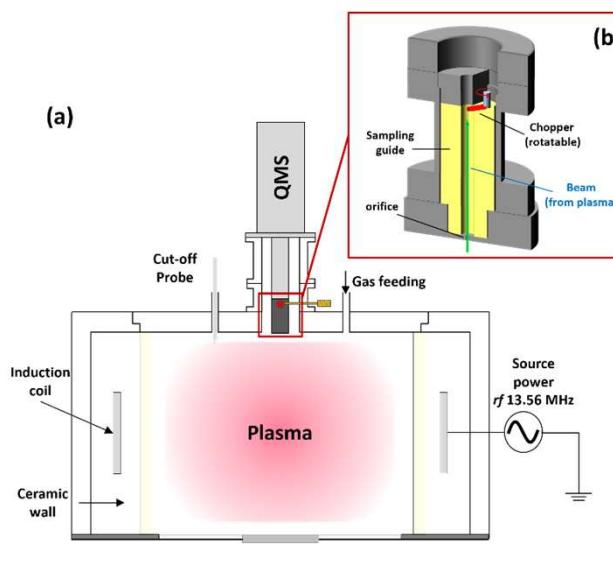
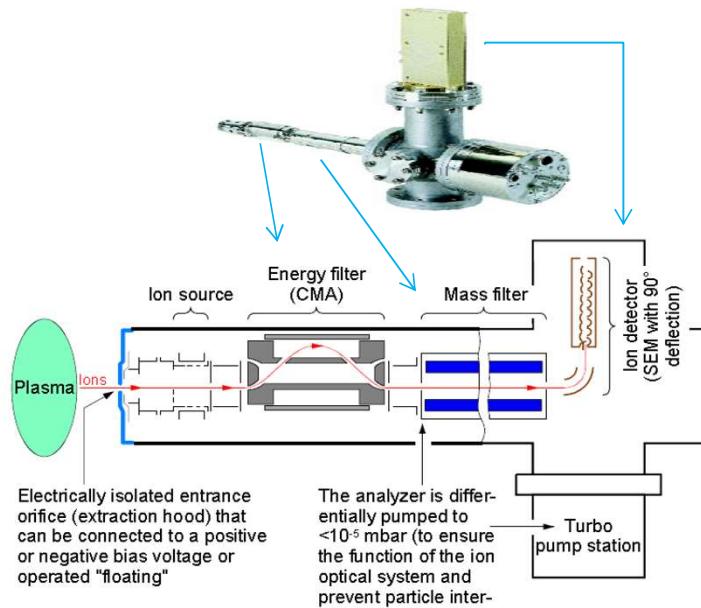
Database development

Software	Key DB
CFD-ACE+	Ar, SiH ₄ /O ₂ /Ar, NF ₃ /Ar, C ₂ F ₆ /O ₂ , CF ₄ , Cl ₂ , He, Ne, N ₂ , O ₂ , Xe, SF ₆ /O ₂
COMSOL	Ar, He, Hg, O ₂
VizGlow	Ar, He, Xe, H ₂ , N ₂ , O ₂ , Ar/O ₂ , Ar/O ₂ /H ₂ , CF ₄ , C ₂ F ₆ , C ₄ F ₈ , CHF ₃ , CF ₄ /O ₂ /He, C ₂ H ₂ /Ar, HBr, SiH ₄ /N ₂ , NF ₃ , NH ₃ /N ₂ /H ₂ /Ar, NF ₃ , NF ₃ /O ₂ , SF ₆ /O ₂ , BF ₃ /Ar
QuantemolDB	N ₂ /H ₂ , Ar/H ₂ , O ₂ /H ₂ , SF ₆ /O ₂ , CF ₄ /O ₂ , CF ₄ /O ₂ /H ₂ /N ₂ , C ₄ F ₈ , SiH ₄ , SiH ₄ /NF ₃ , Ar/O ₂ , Ar/O ₂ /C ₄ F ₈ , SiH ₄ /Ar/O ₂ , Ar/Cu, Cl ₂ /O ₂ /Ar, Ar/BCl ₃ /Cl ₂ , Ar/NF ₃ , CH ₄ /H ₂ , C ₂ H ₂ /H ₂ , CH ₄ /NF ₃ , H ₂ /O ₂ , CF ₄ /CHF ₃ /H ₂ /Cl ₂ /O ₂ /HBr, SF ₆ /CF ₄ /O ₂ , Ar/Cu/He, Ar/NF ₃ , SF ₆ /CF ₄ /N ₂ /H ₂
K-SPEED	C _{x1} F _{y1} /C _{x2} F _{y2} /CH _x F _y /O ₂ /Ar, NF ₃ /Ar, SiH ₄ /O ₂ /Ar

2. Plasma Modeling

Database development

- APMS (appearance potential mass spectrometry) method and the microwave cut-off probe
- Reducing the back-ground noise inside the QMS by using a chopper (W. S. Chang et al, **to be published**)



2. Plasma Modeling

Global model

$$\frac{\partial n_i}{\partial t} = \sum_j R_{g,j} + \frac{Q_i}{\Omega} - \sum_j R_{l,j} - n_i \left(\frac{V_{pump}}{\Omega} + V_l^i \right)$$

$$\frac{\partial}{\partial t} \left(N c_p T_g \right) = \sum_i 3 n_e V_m \left(\frac{m_e}{m_i} \right) k_B (T_e - T_g) + \sum_j n_e k_j n_j \Delta E_j - \sum_j \Delta H_j - \frac{h_{lc} A}{\Omega} (T_g - T_w)$$

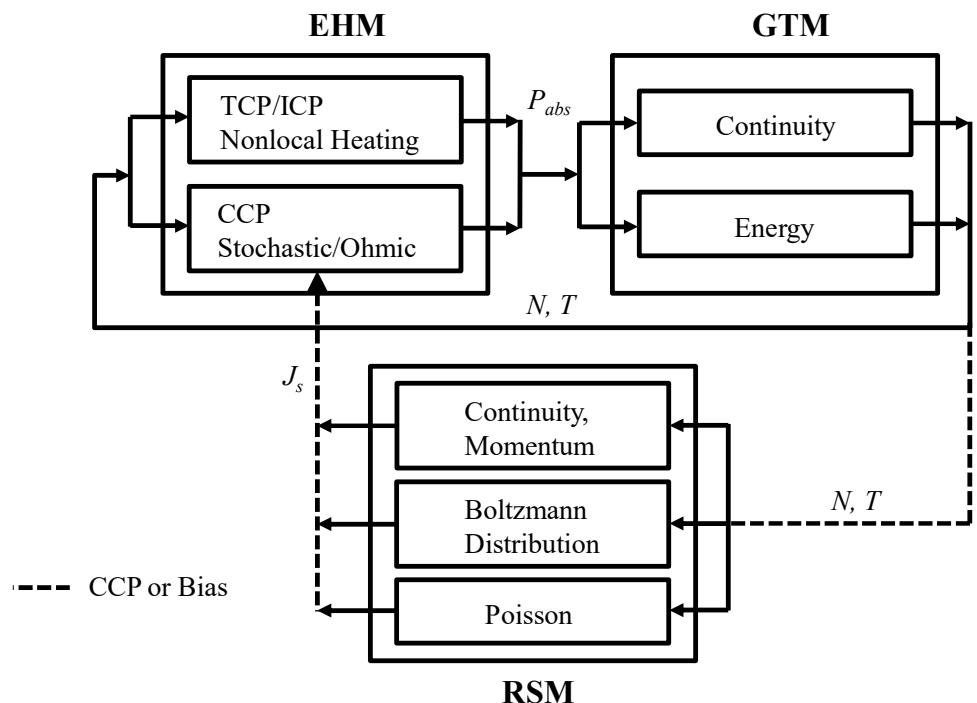
When the EEDF is given,

$$\frac{\partial}{\partial t} \left(\frac{3}{2} n_e T_e \right) = \frac{P_{abs}}{\Omega} - E_e - n_e \varepsilon_l^e V_l^e$$

When the EEDF is solved in a self-consistent manner,

$$T_e = \frac{2}{3} \langle \varepsilon \rangle = \frac{2}{3 n_e} \int_0^\infty \varepsilon^{3/2} f_0(\varepsilon) d\varepsilon$$

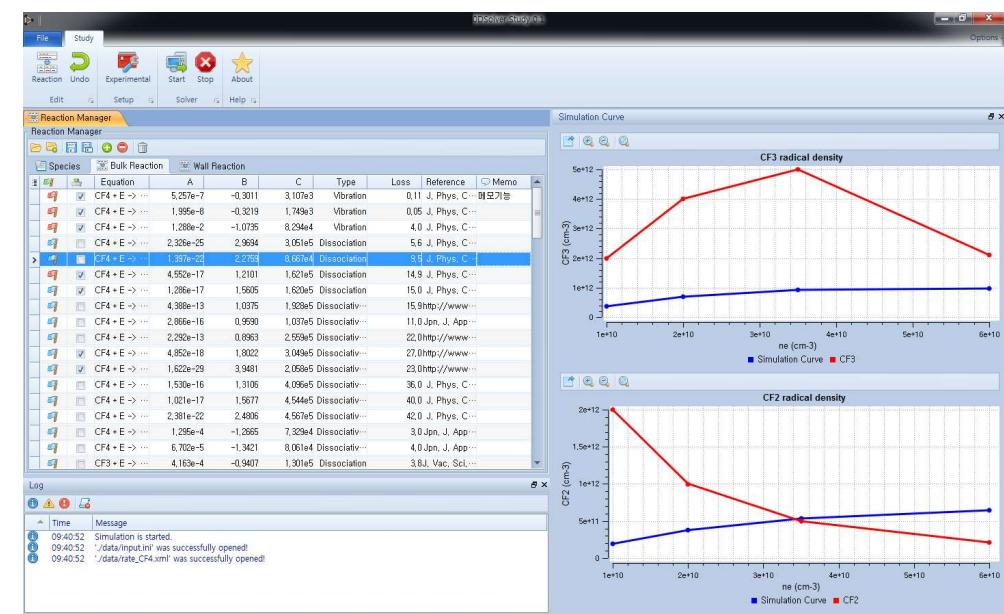
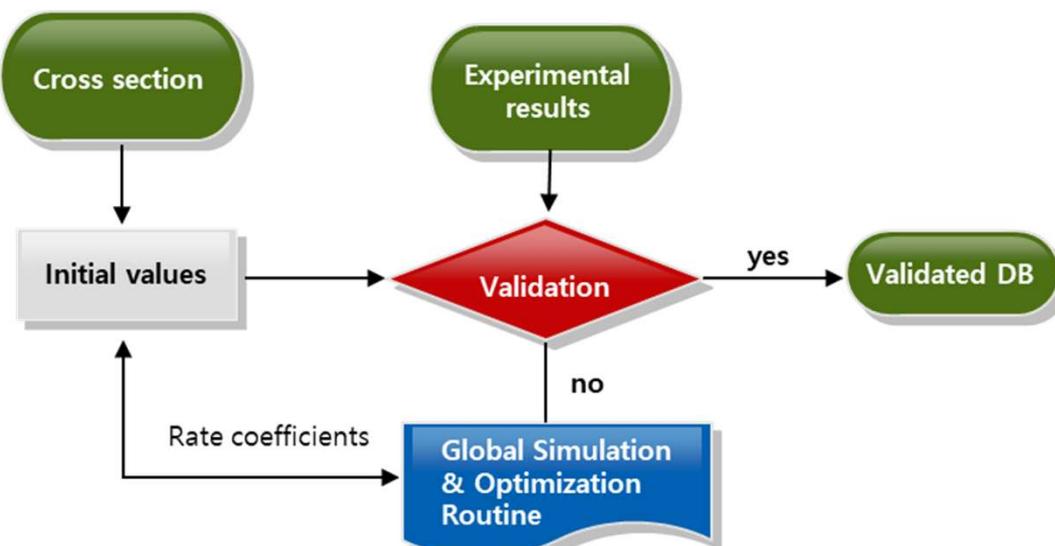
$$k = \int_0^\infty f_0(\varepsilon) \sigma(\varepsilon) v d\varepsilon, \quad R = k \times \prod_j n_{r,j}, \quad V_l^i = \frac{A_{eff}}{\Omega} \sqrt{\frac{k_B T_e (1 + \alpha_s)}{m_i (1 + \alpha_s \gamma_-)}}, \quad A_{eff} = 2\pi (R_p^2 h_L + R_p L_p h_R)$$



2. Plasma Modeling

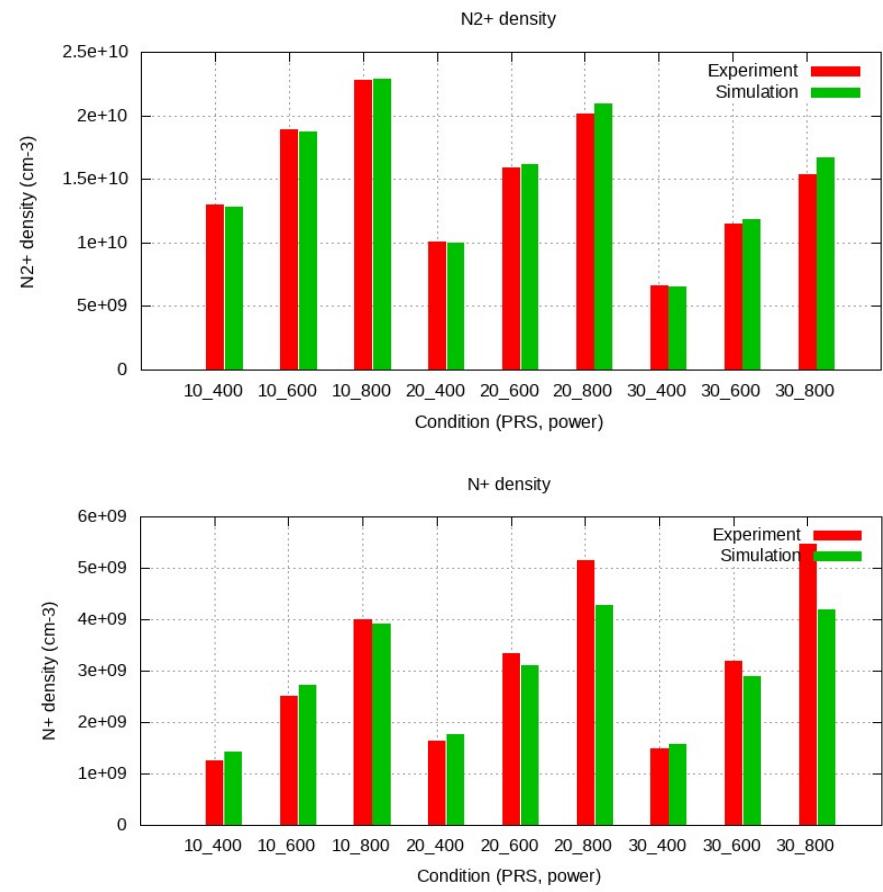
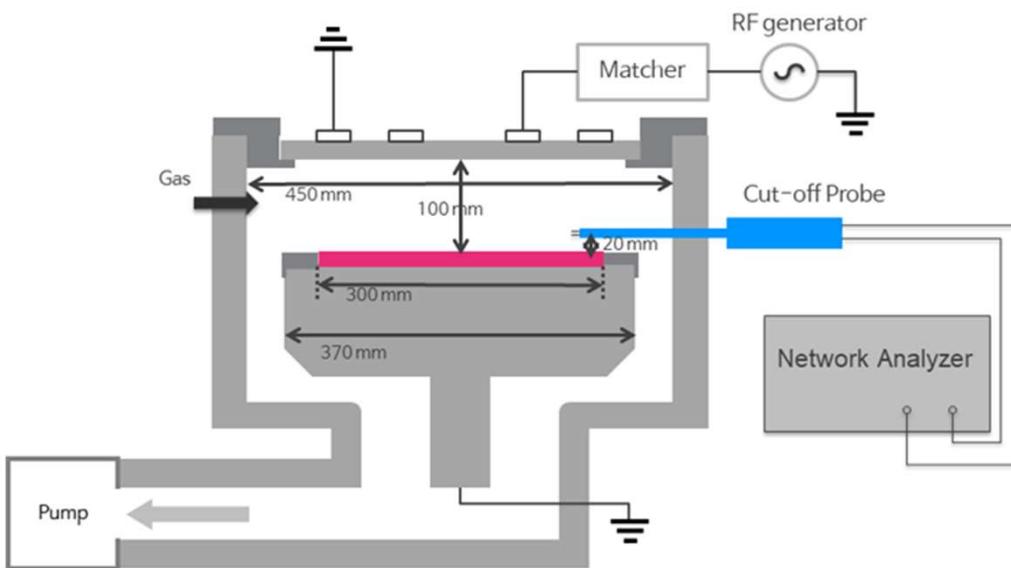
Global model

- Optimized the rate coefficients for heavy particle reactions excluding electron collisions.
- Numerical optimization (Random sampling, Newton, Secan, Broyden-Fletcher-Goldfarb-Shanno, etc.)



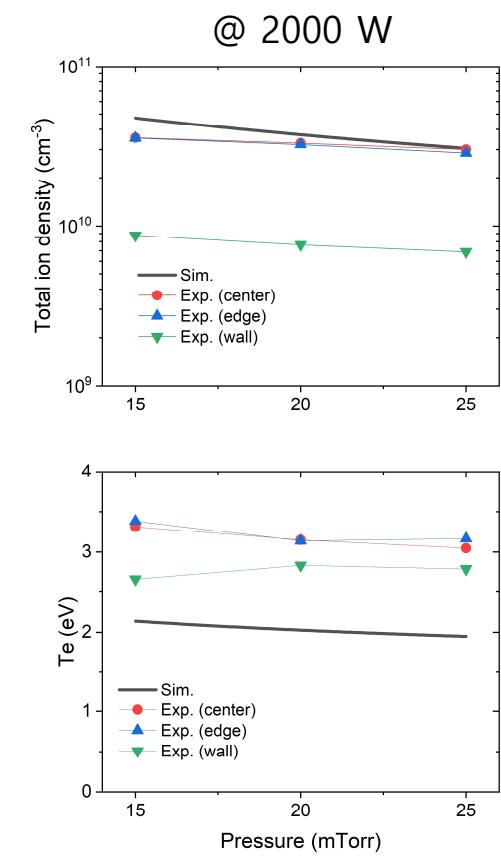
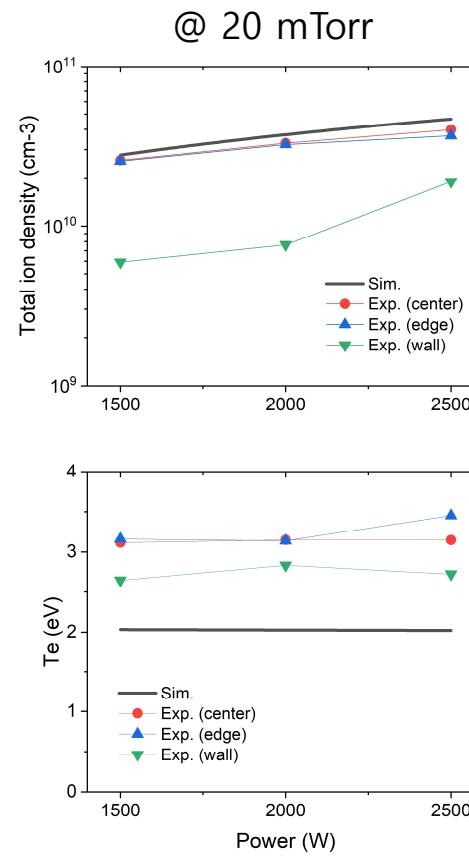
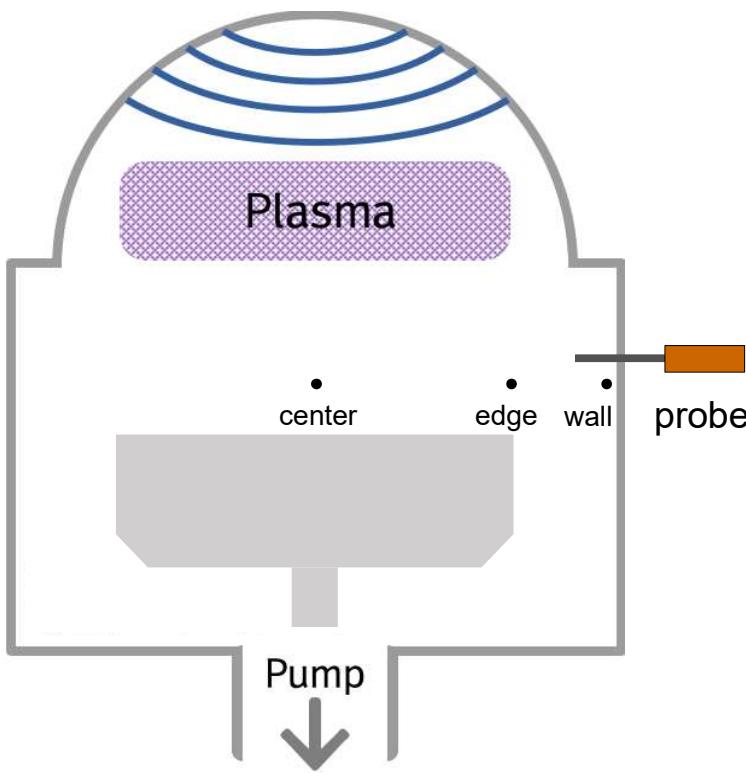
2. Plasma Modeling

Global model @ N₂ discharges



2. Plasma Modeling

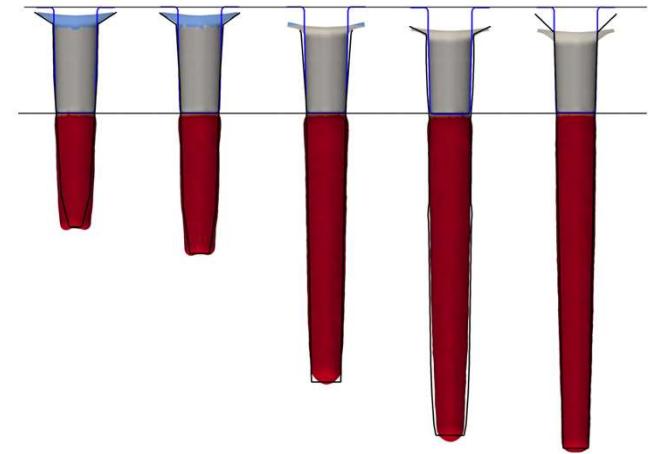
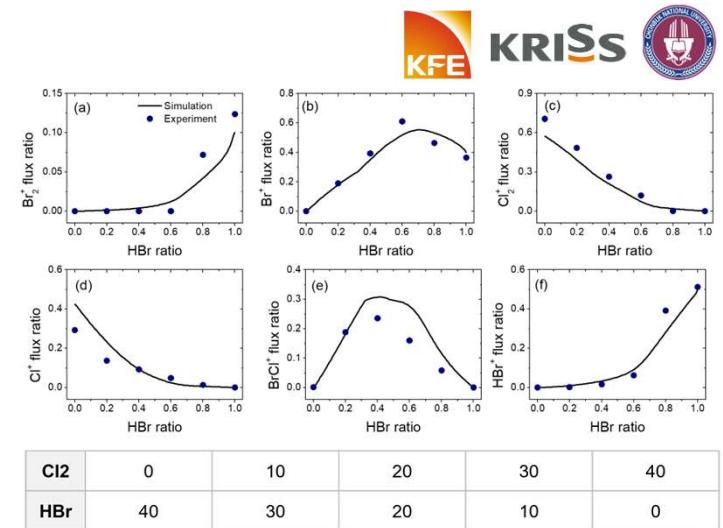
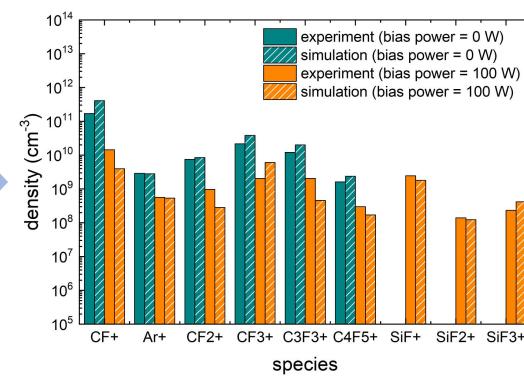
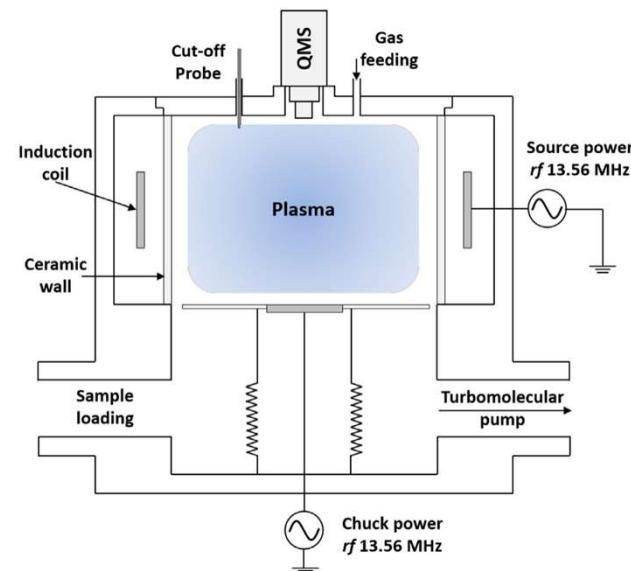
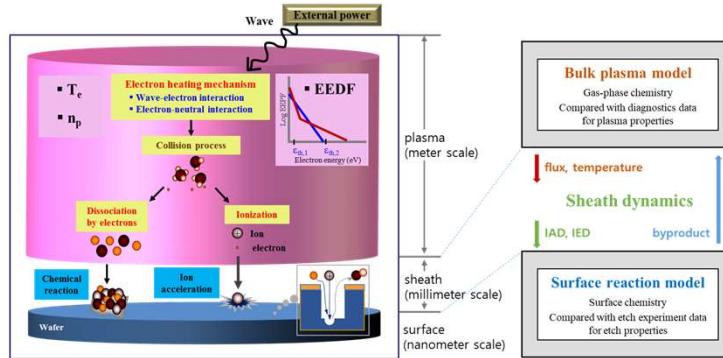
Global model @ commercial source



2. Plasma Modeling

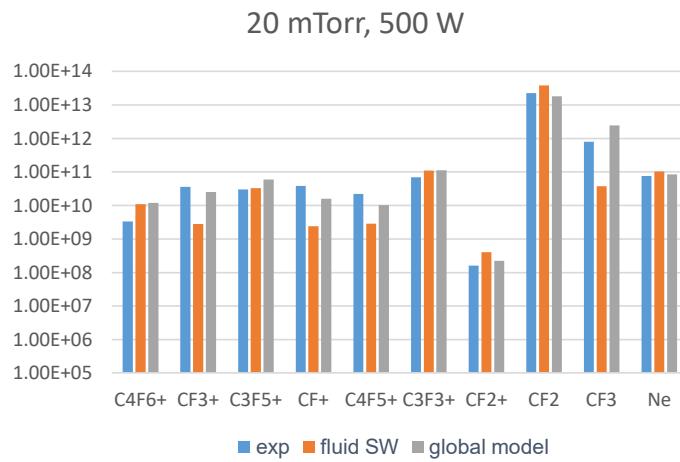
Global model

6 inch oxide wafer

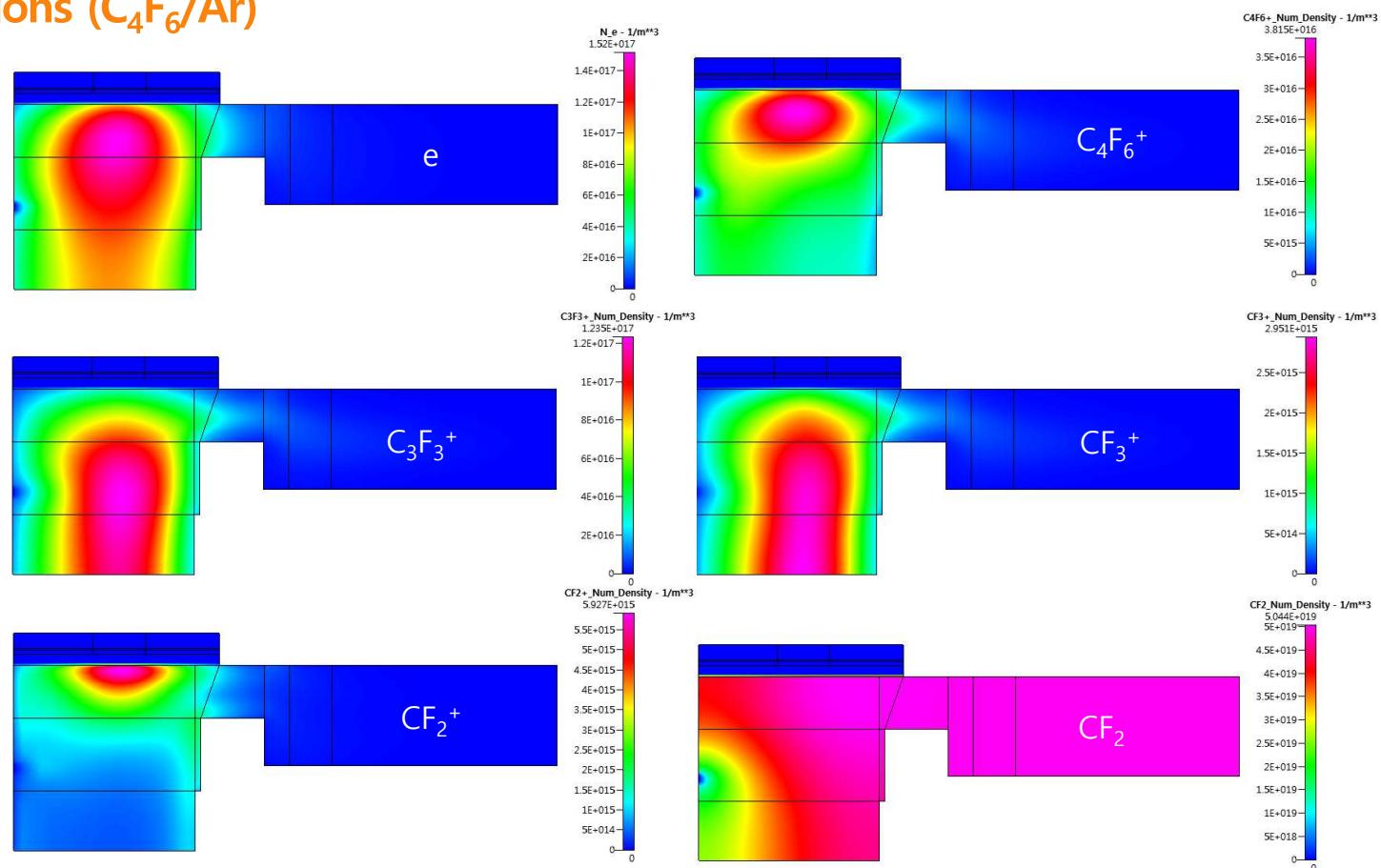
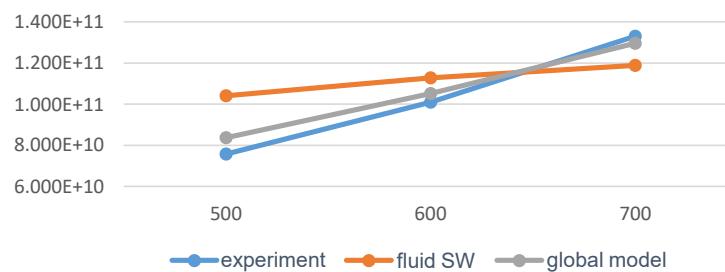


2. Plasma Modeling

Comparison with 2D simulations (C_4F_6/Ar)



Plasma Density



2. Plasma Modeling

Developed bulk database

Gas	DB	experiment	validated
C ₄ F ₆ /Ar	0	0	0
C ₄ F ₆ /Cl ₂ /Ar	0	0	0
C ₄ F ₈ /Ar	0	0	0
C ₄ F ₆ /C ₄ F ₈ /Ar	0	0	0
C ₄ F ₆ /O ₂ /Ar	0	0	0
C ₄ F ₆ /C ₄ F ₈ /O ₂	0	0	0
C ₄ F ₆ /C ₄ F ₈ /CH ₂ F ₂ /O ₂	0	0	0
C ₄ F ₆ /C ₄ F ₈ /CH ₂ F ₂ /O ₂ /Ar	0	0	0
C ₄ F ₆ /C ₄ F ₈ /CH ₂ F ₂ /Ar	0	0	0
C ₄ F ₆ /C ₄ F ₈ /CHF ₃ /Ar	0	0	0
C ₄ F ₆ /C ₄ F ₈ /CH ₃ F/Ar	0	0	0
C ₄ F ₆ /C ₄ F ₈ /C ₃ F ₈ /Ar	0	0	0
CHF ₃ /Ar	△	X	△
C ₂ HF ₅ /Ar	0	0	0
CH ₂ F ₂ /Ar	0	0	0
SiH ₄ /Ar	0	0	0
SiH ₄ /NH ₃ /Ar	0	0	0

Gas	DB	experiment	validated
N ₂	0	0	0
Ar	0	0	0
CF ₄ /O ₂	0	△	0
CF ₄ /Cl ₂	△	X	△
PF ₃	△	X	△
SF ₆	△	X	△
WF ₆	△	X	△
Kr	△	X	△
Xe	△	X	△
CBr ₂ F ₂	△	X	△
NF ₃ /O ₂ /Ar	0	0	0
HBr/Cl ₂	0	△	0
C ₄ F ₈ /CHF ₃ /Kr	0	0	0
C ₄ F ₈ /CH ₂ F ₂ /O ₂ /Xe	0	0	0
C ₄ F ₈ /CH ₂ F ₂ /O ₂ /Ar(Kr)	0	0	X
SiH ₄ /H ₂ /Ar	0	0	X
Etc	△	△	△

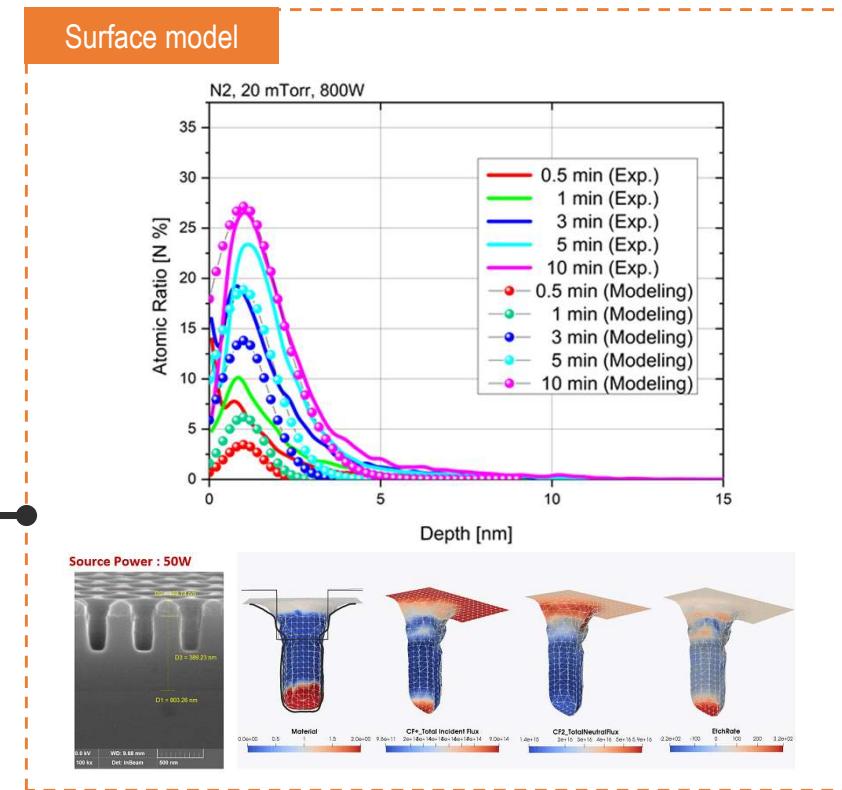
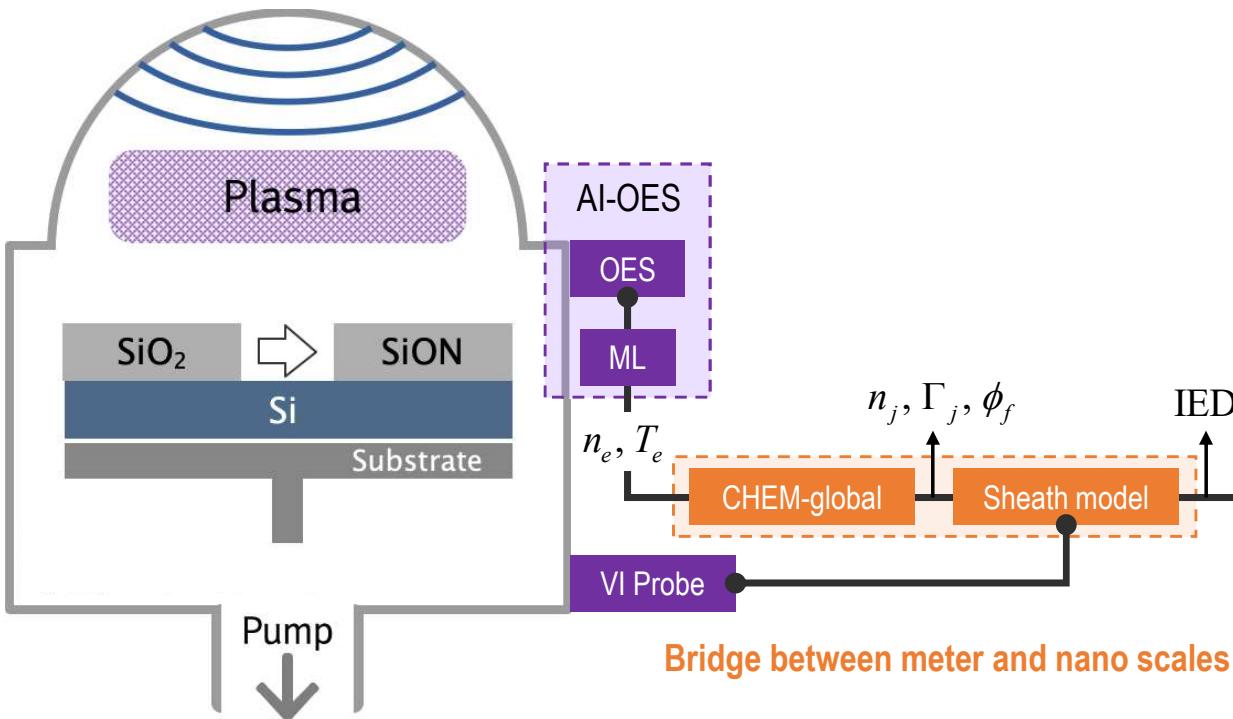
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ML-aided Modeling



3. ML-aided Modeling

Sensor-bulk-surface coupling model



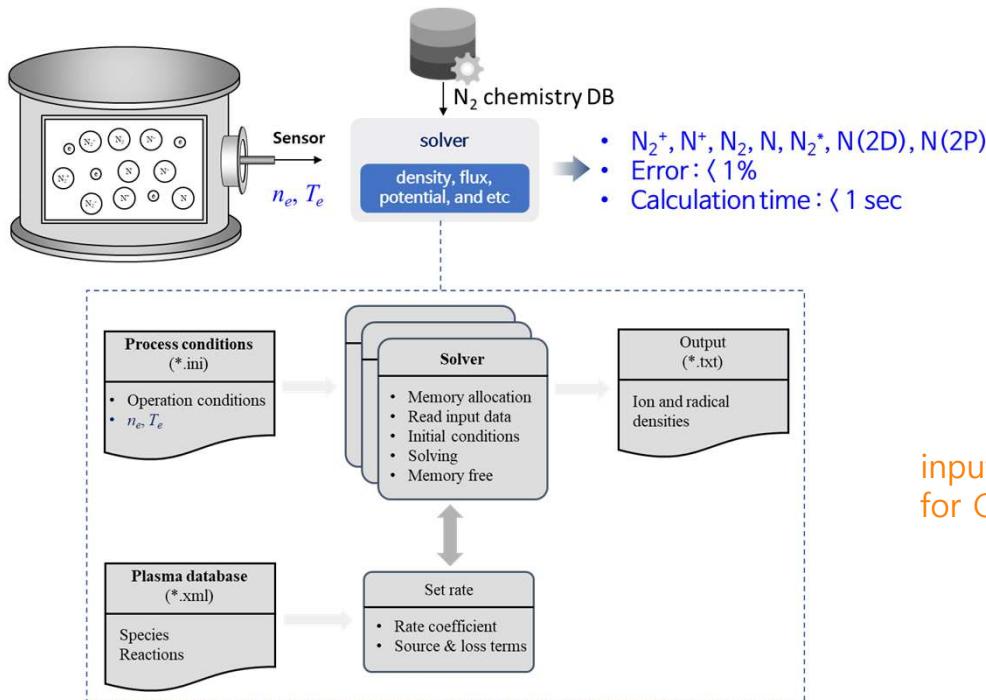
3. ML-aided Modeling

CHEM-global (chemical reaction analyzer using a global model)

- Quasi-neutrality

Assuming the quasi-neutrality, the continuity equation is solved using the electron density and temperature.

@ N₂ 80 SCCM, 15 mTorr, 500 W



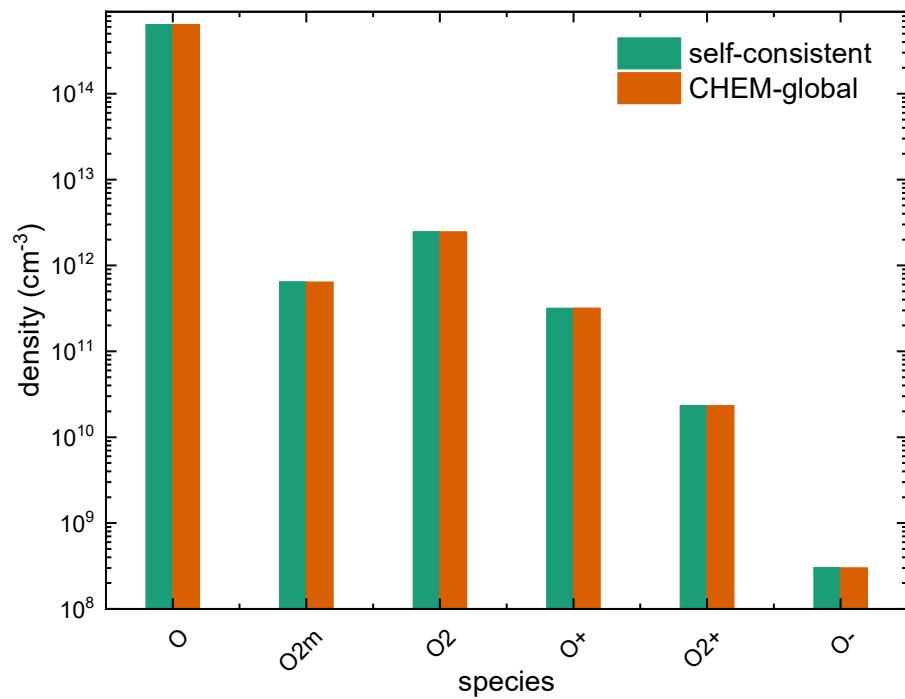
input parameters
for CHEM-global

species	Self-consistent	CHEM-global
N	$1.5166 \times 10^{13} \text{ cm}^{-3}$	$1.5164 \times 10^{13} \text{ cm}^{-3}$
N ₂ [*]	$7.3827 \times 10^{12} \text{ cm}^{-3}$	$7.3815 \times 10^{12} \text{ cm}^{-3}$
N ₂	$4.6440 \times 10^{14} \text{ cm}^{-3}$	$4.6432 \times 10^{14} \text{ cm}^{-3}$
N(2P)	$6.9623 \times 10^{11} \text{ cm}^{-3}$	$6.9603 \times 10^{11} \text{ cm}^{-3}$
N(2D)	$1.3143 \times 10^{12} \text{ cm}^{-3}$	$1.3141 \times 10^{12} \text{ cm}^{-3}$
N ₂ ⁺	$6.0594 \times 10^{10} \text{ cm}^{-3}$	$6.0595 \times 10^{10} \text{ cm}^{-3}$
N ⁺	$2.4852 \times 10^9 \text{ cm}^{-3}$	$2.4850 \times 10^9 \text{ cm}^{-3}$
e	$6.3080 \times 10^{10} \text{ cm}^{-3}$	
T _e	2.9531 eV	
Calculation time	161 sec	0.001 sec

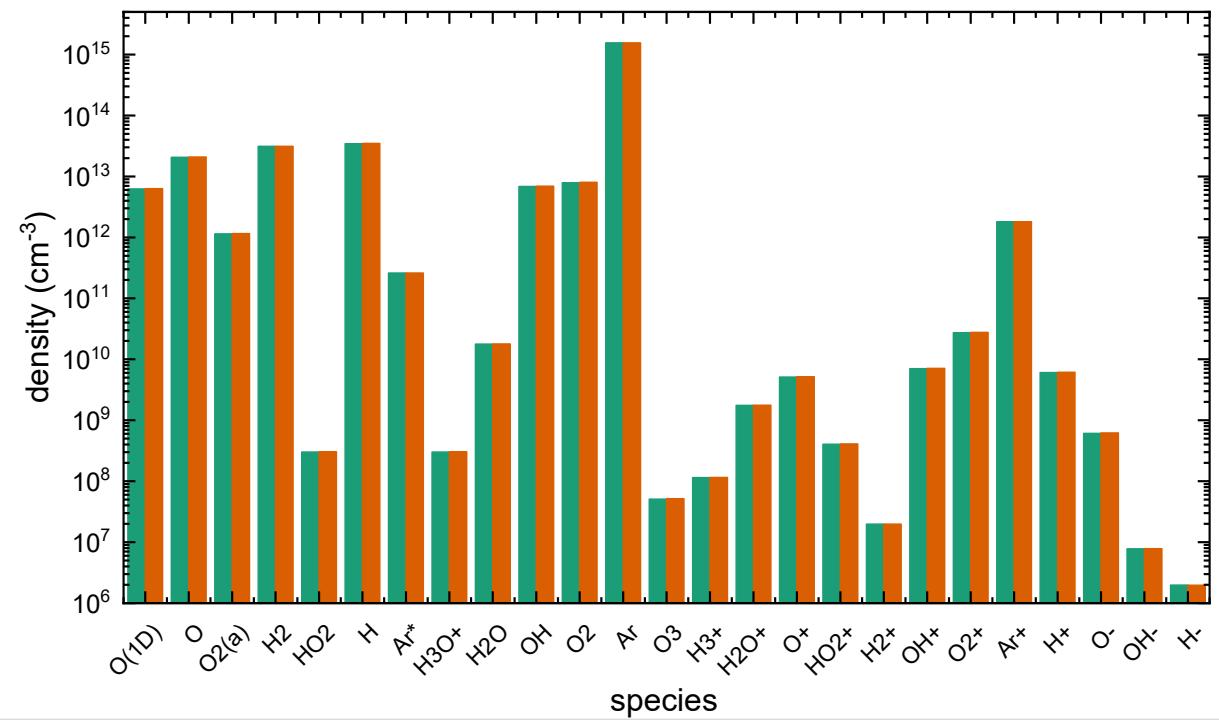
3. ML-aided Modeling

CHEM-global

- O₂ plasma
 - 7 species and 25 reactions
 - O₂ 80 SCCM, 10 mTorr, 500 W → 0.5% mean error

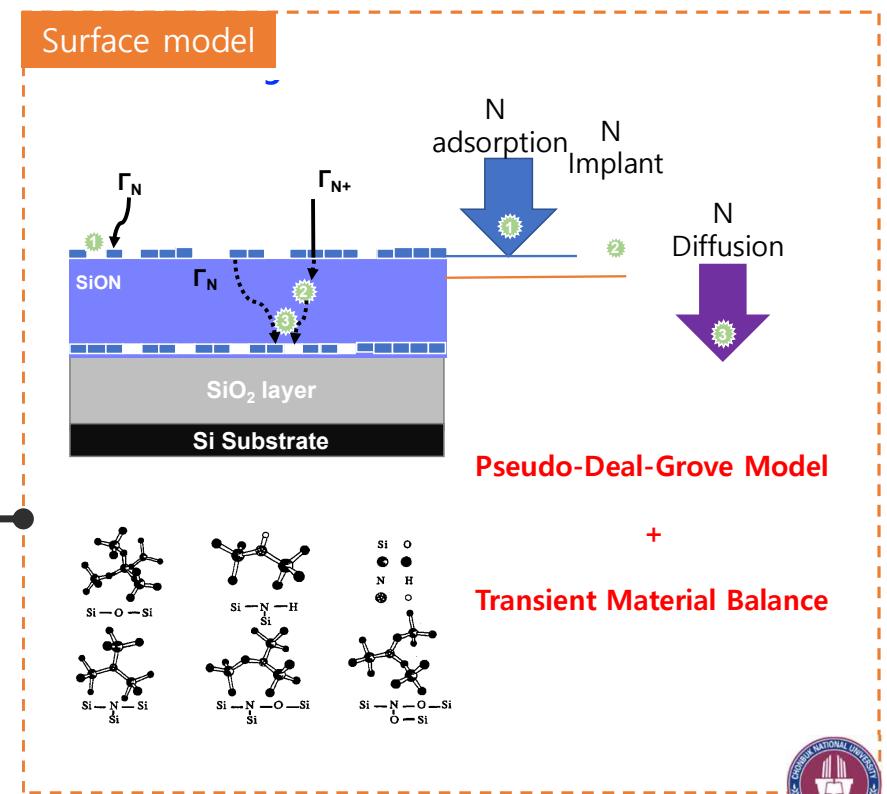
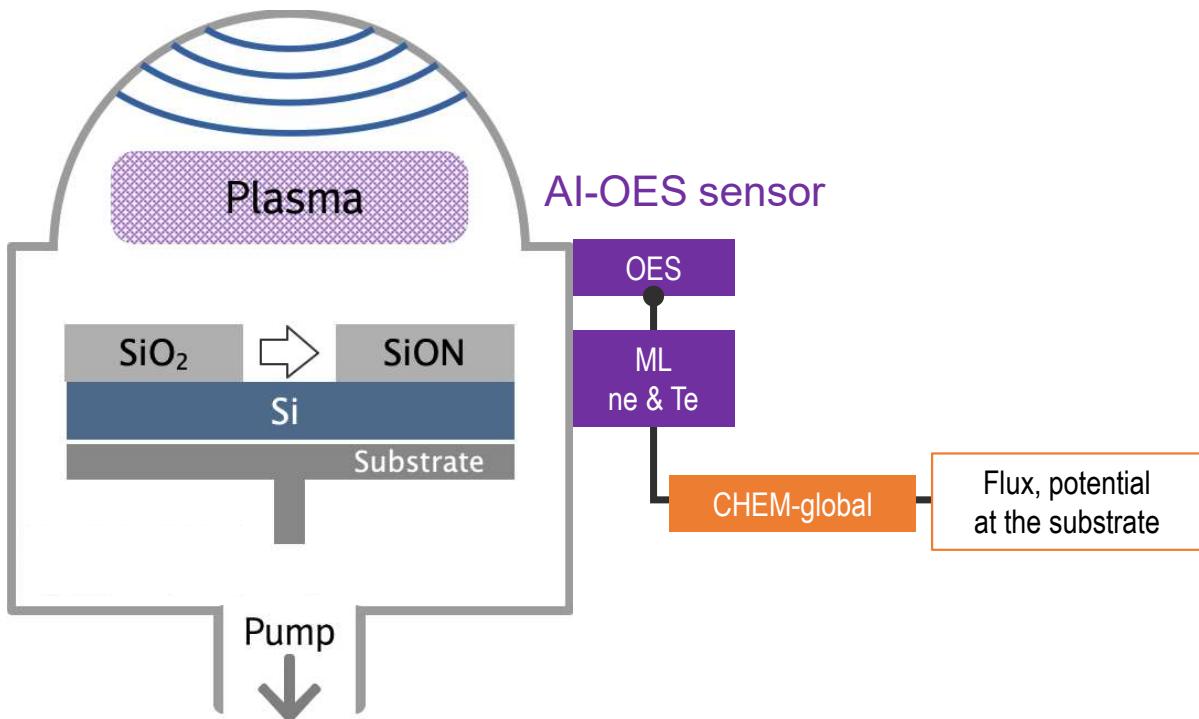


- H₂O/Ar plasma
 - 26 species and 153 reactions
 - H₂O 1 SCCM, Ar 30 SCCM, 50 mTorr, 1500 W → 0.8% mean error



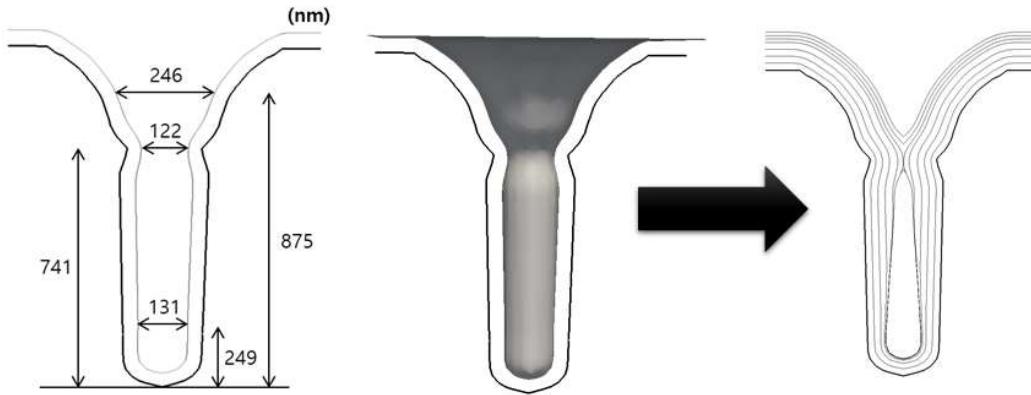
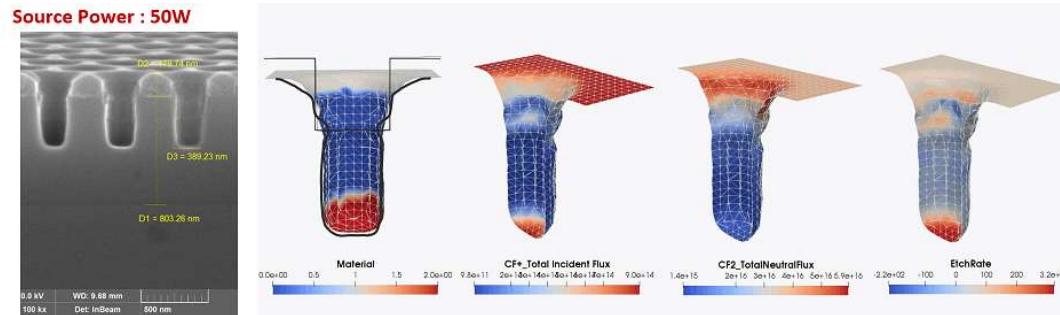
3. ML-aided Modeling

Bulk-surface coupling model

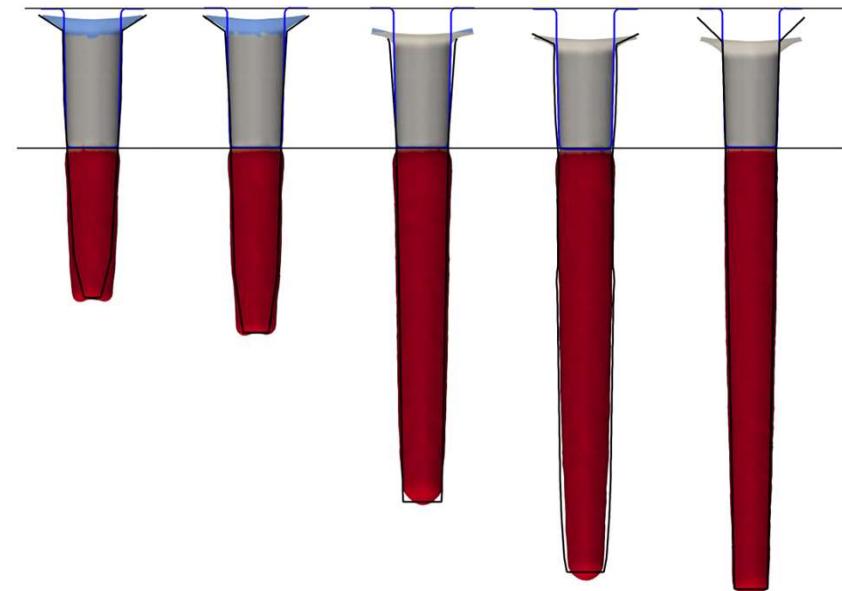


3. ML-aided Modeling

Bulk-surface coupling model

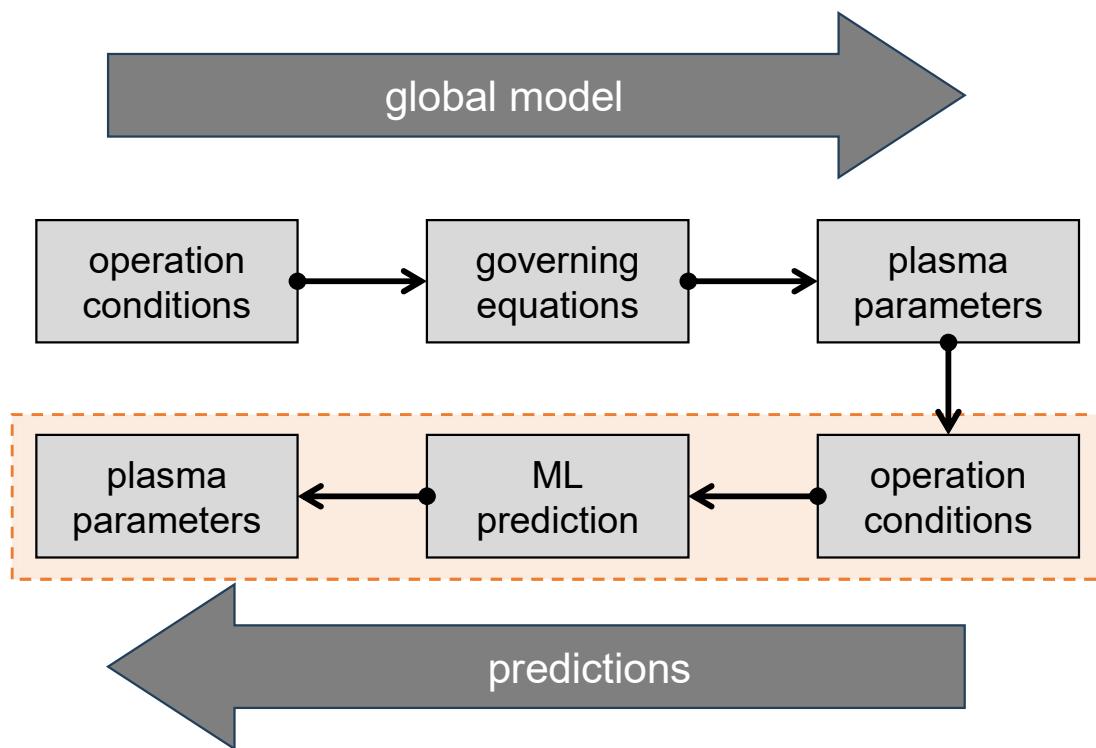


Cl2	0	10	20	30	40
HBr	40	30	20	10	0

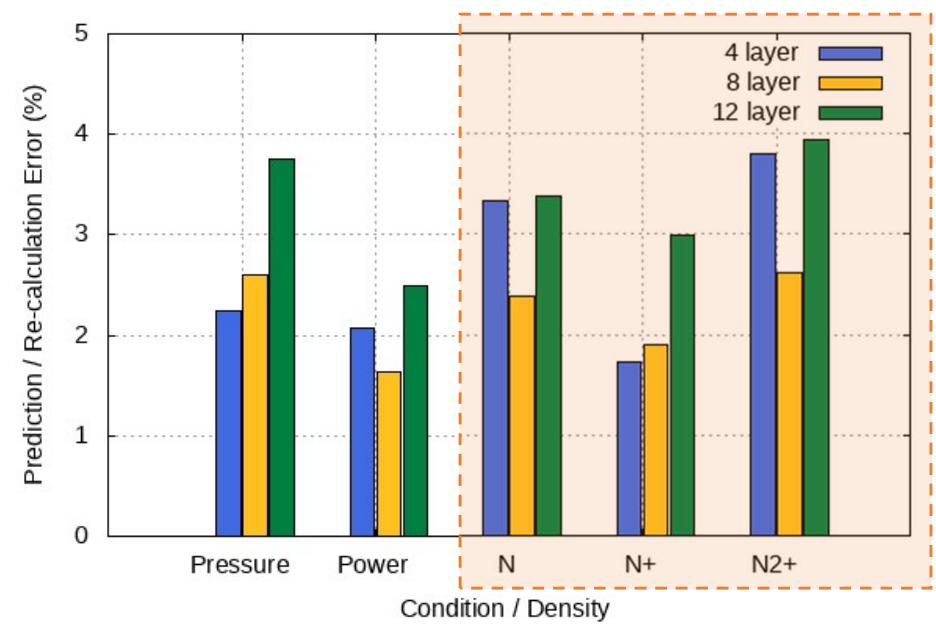


3. ML-aided Modeling

Global model + Machine learning

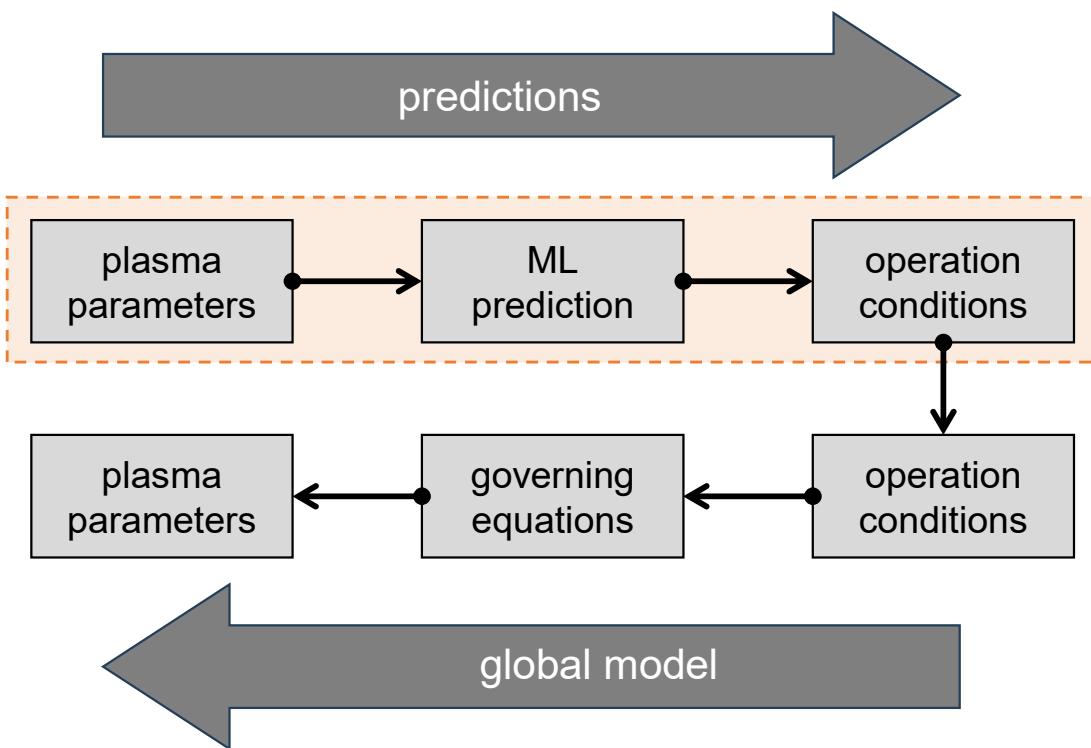


- Training plasma parameters on operations → prediction of plasma parameters
- Accuracy is not always proportional to the number of hidden layers

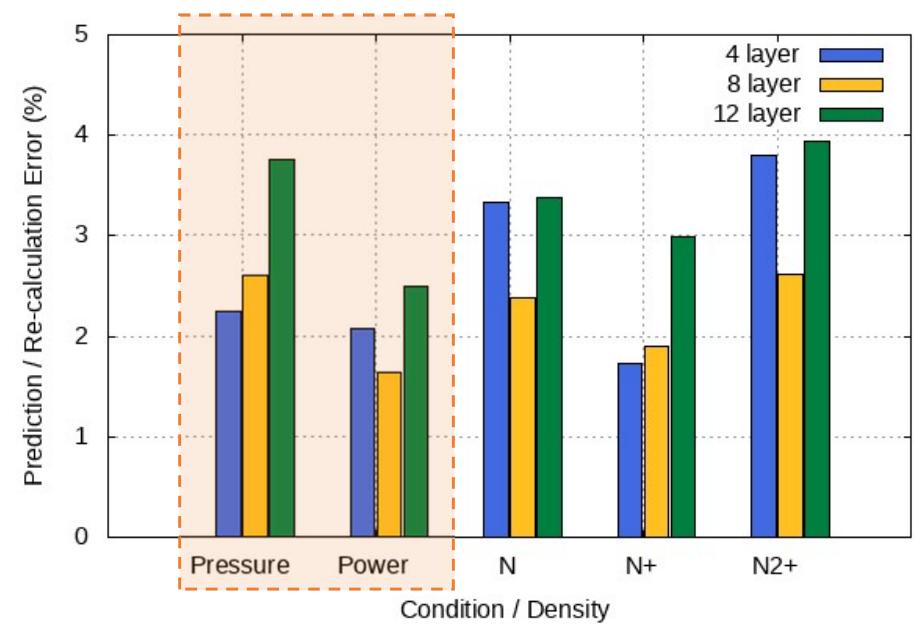


3. ML-aided Modeling

Global model + Machine learning



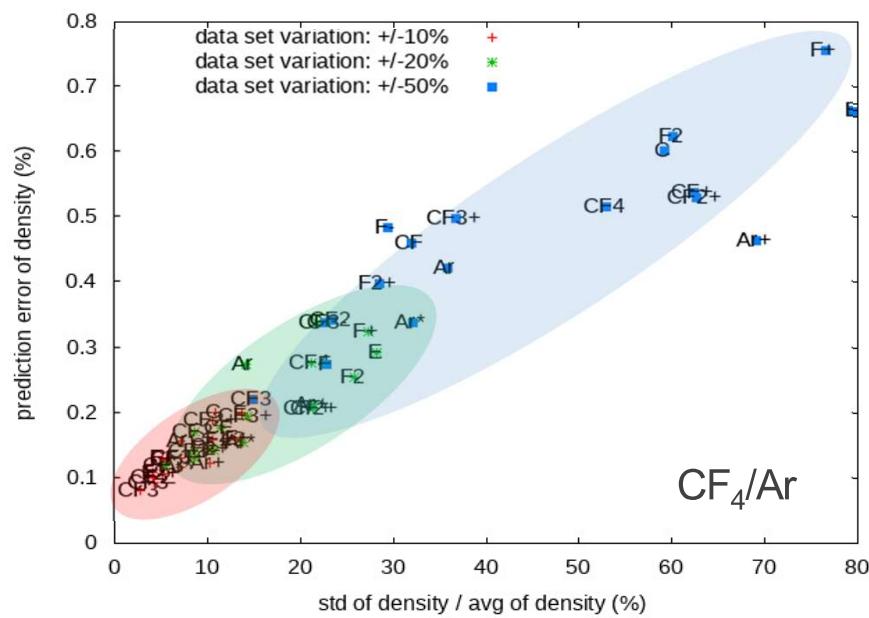
- Inversely, training operation conditions on plasma parameters
- Prediction of operation conditions for a target plasma



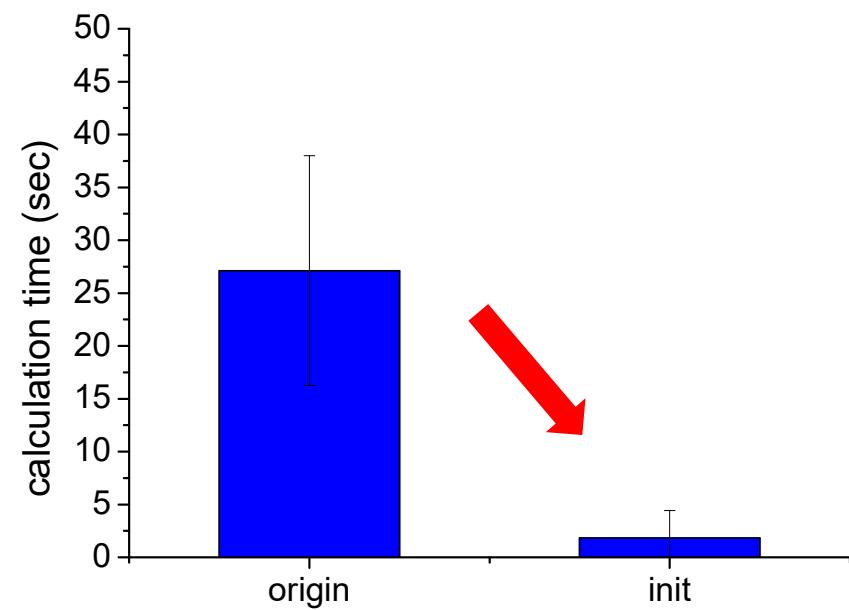
3. ML-aided Modeling

Global model + Machine learning

- Global model → training → prediction
 - Prediction errors \propto data set variation
 - Sensitive species on input conditions → error ↑



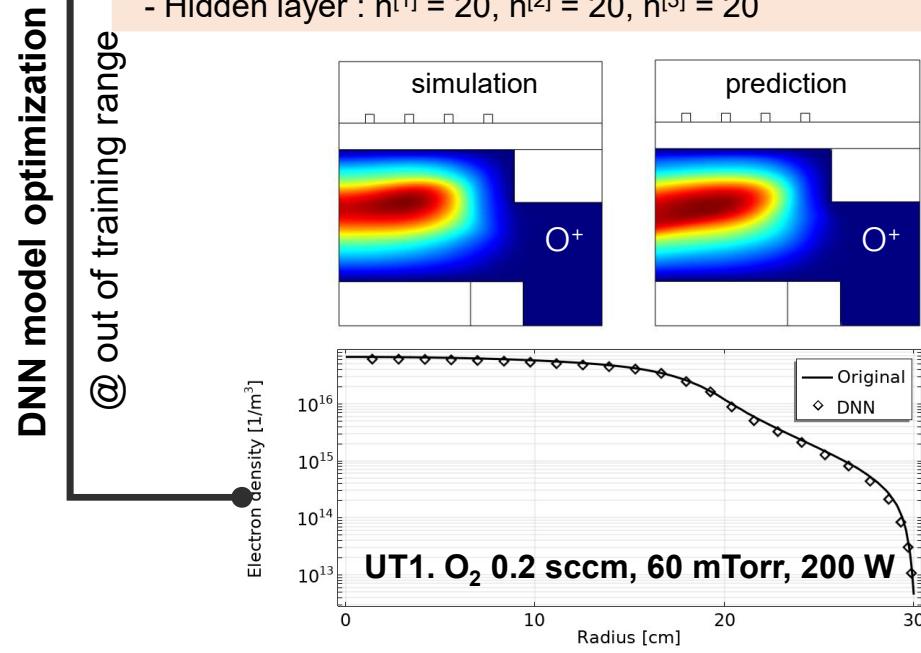
- ML prediction → global model
 - Predicted values → set to be initial values
 - Improved computational efficiency



3. ML-aided Modeling

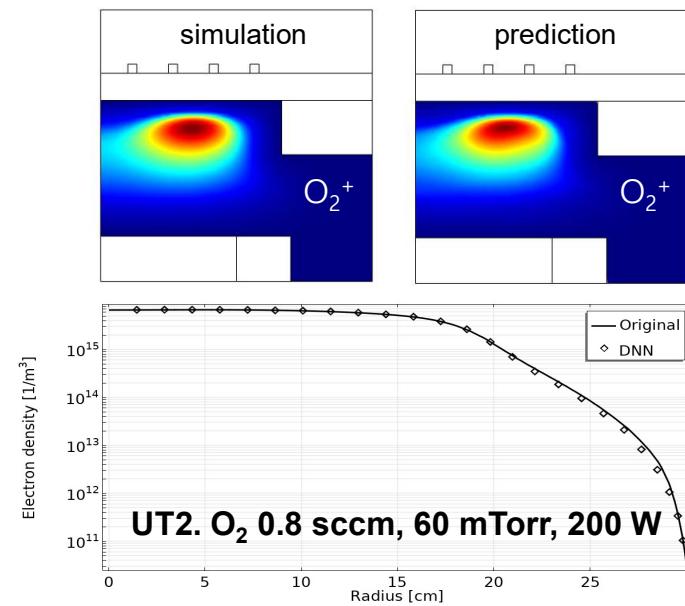
Neural network for ICP sources

- Z-score normalization for input data
- Log normalization for output data
- Train type : Bayesian regulation (Trainbr)
- Train network : feedforward net
- Activate function type : rectified linear unit (ReLU)
- Hidden layer : $n^{[1]} = 20, n^{[2]} = 20, n^{[3]} = 20$



Conditions :

- Ar/ O_2 total 250 sccm
- O_2 flow rate = 0.3, 0.4, 0.5, 0.6, 0.7 sccm
- Power = 100, 120, 140, 160, 180 W
- Pressure = 10, 20, 30, 40, 50 mTorr

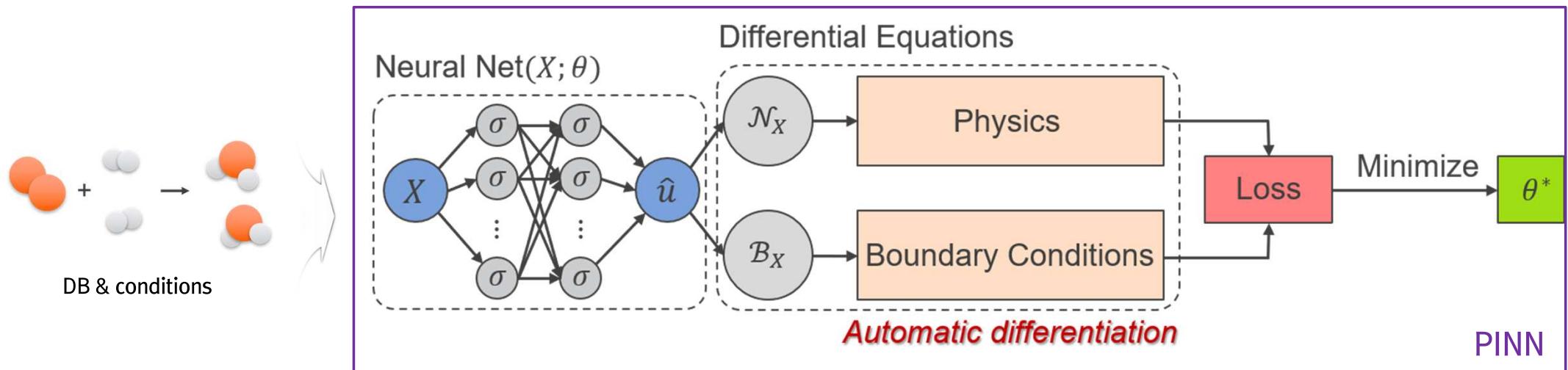


3. ML-aided Modeling

Physics-informed neural networks (PINNs)



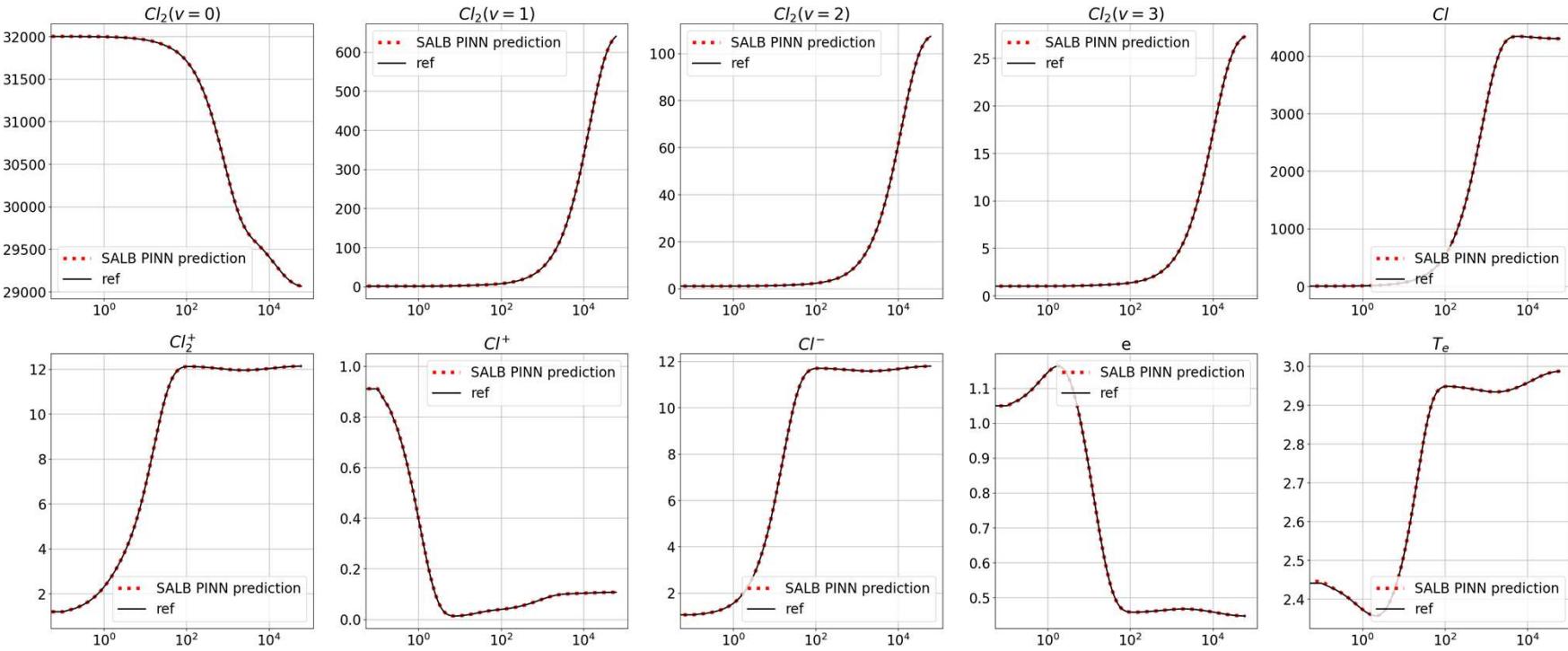
- Intersection of the traditional physics model and the purely data-driven neural network approach.
- Physical parameters can be obtained without solving governing equations directly.
- DB (required), discretization (partially unnecessary) → lower barriers to entry into simulations



3. ML-aided Modeling

Physics-informed neural networks (PINNs)

- Forward problem, Normalization
- Naive PINNs → Learn only some variable → SALB (self adaptive loss balance) loss function



3. ML-aided Modeling

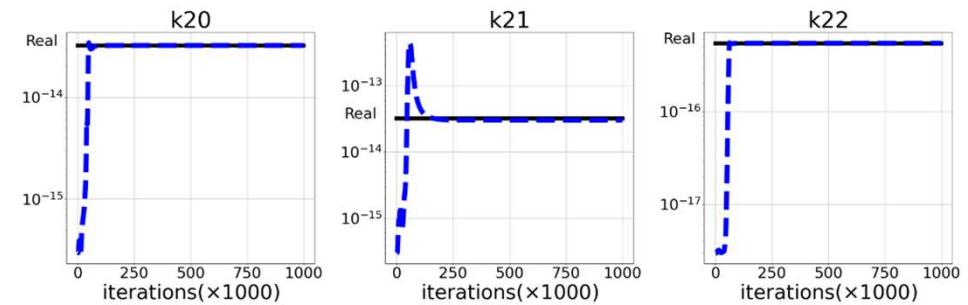
Physics-informed neural networks (PINNs)

- Inverse problem to find rate coefficients

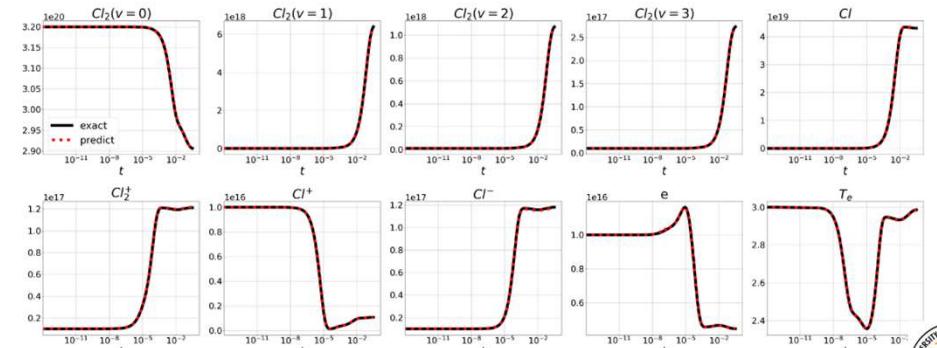
Reaction	Rate coefficient ($\text{m}^3 \text{s}^{-1}$ or $\text{m}^6 \text{s}^{-1}$)
(R1) $e + Cl_2(v = 0) \rightarrow Cl + Cl + e$	$6.67 \times 10^{-14} T_e^{-0.10} e^{-8.67/T_e}$
(R2) $e + Cl_2(v = 0) \rightarrow Cl_2^+ + e + e$	$4.87 \times 10^{-14} T_e^{0.50} e^{-12.17/T_e}$
(R3) $e + Cl_2(v = 0) \rightarrow Cl + Cl^+ + 2e$	$1.79 \times 10^{-13} e^{-24.88/T_e}$
(R4) $e + Cl_2(v = 0) \rightarrow Cl^+ + Cl^+ + 3e$	$1.46 \times 10^{-16} T_e^{2.16} e^{-21.42/T_e}$
(R5) $e + Cl_2(v = 0) \rightarrow Cl + Cl^-$	$(22.5T_e^{-0.46} e^{-2.82/T_e} - 12.1 e^{-0.99/T_e} + 6.54) \times 10^{-16}$
(R6) $e + Cl_2(v = 1) \rightarrow Cl + Cl^-$	$(9.29T_e^{-0.47} e^{-2.83/T_e} - 4.96 e^{-0.99/T_e} + 2.70) \times 10^{-15}$
(R7) $e + Cl_2(v = 2) \rightarrow Cl + Cl^-$	$(20.1T_e^{-0.47} e^{-2.83/T_e} - 10.8 e^{-0.97/T_e} + 5.92) \times 10^{-15}$
(R8) $e + Cl_2(v = 3) \rightarrow Cl + Cl^-$	$(30.5T_e^{-0.46} e^{-2.82/T_e} - 16.3 e^{-0.99/T_e} + 8.81) \times 10^{-15}$
(R9) $e + Cl_2(v = 0) \rightarrow Cl^+ + Cl^- + e$	$3.45 \times 10^{-16} T_e^{0.13} e^{-19.70/T_e}$
(R10) $e + Cl_2(v = 0) \rightarrow Cl_2(v = 1) + e$	$4.35 \times 10^{-16} T_e^{-1.48} e^{-0.76/T_e}$
(R11) $e + Cl_2(v = 0) \rightarrow Cl_2(v = 2) + e$	$8.10 \times 10^{-17} T_e^{-1.48} e^{-0.68/T_e}$
(R12) $e + Cl_2(v = 0) \rightarrow Cl_2(v = 3) + e$	$2.39 \times 10^{-17} T_e^{-1.49} e^{-0.64/T_e}$
(R13) $e + Cl_2(v = 1) \rightarrow Cl_2(v = 2) + e$	$1.04 \times 10^{-15} T_e^{-1.48} e^{-0.73/T_e}$
(R14) $e + Cl_2(v = 1) \rightarrow Cl_2(v = 3) + e$	$2.98 \times 10^{-16} T_e^{-1.48} e^{-0.67/T_e}$
(R15) $e + Cl_2(v = 2) \rightarrow Cl_2(v = 3) + e$	$1.04 \times 10^{-15} T_e^{-1.48} e^{-0.73/T_e}$
(R16) $e + Cl \rightarrow Cl^+ + e + e$	$2.48 \times 10^{-14} T_e^{0.62} e^{-12.76/T_e}$
(R17) $e + Cl^- \rightarrow Cl + e + e$	$2.33 \times 10^{-15} T_e^{1.45} e^{-2.48/T_e}$
(R18) $e + Cl^- \rightarrow Cl^+ + 3e$	$3.38 \times 10^{-15} T_e^{0.75} e^{-25.28/T_e}$
(R19) $e + Cl_2^+ \rightarrow Cl + Cl$	$9.00 \times 10^{-14} T_e^{-0.50}$
(R20) $Cl_2^+ + Cl^- \rightarrow Cl + Cl + Cl$	$5.00 \times 10^{-14} (300/T_g)^{0.50}$
(R21) $Cl^+ + Cl^- \rightarrow Cl + Cl$	$5.00 \times 10^{-14} (300/T_g)^{0.50}$
(R22) $Cl_2 + Cl^+ \rightarrow Cl_2^+ + Cl$	5.40×10^{-16}
(R23) $2Cl + Cl_2 \rightarrow Cl_2(v = 0) + Cl_2$	$3.50 \times 10^{-45} e^{810/T_g}$
(R24) $2Cl + Cl \rightarrow Cl_2(v = 0) + Cl$	$8.75 \times 10^{-46} e^{810/T_g}$



Results of k 's values over iterations



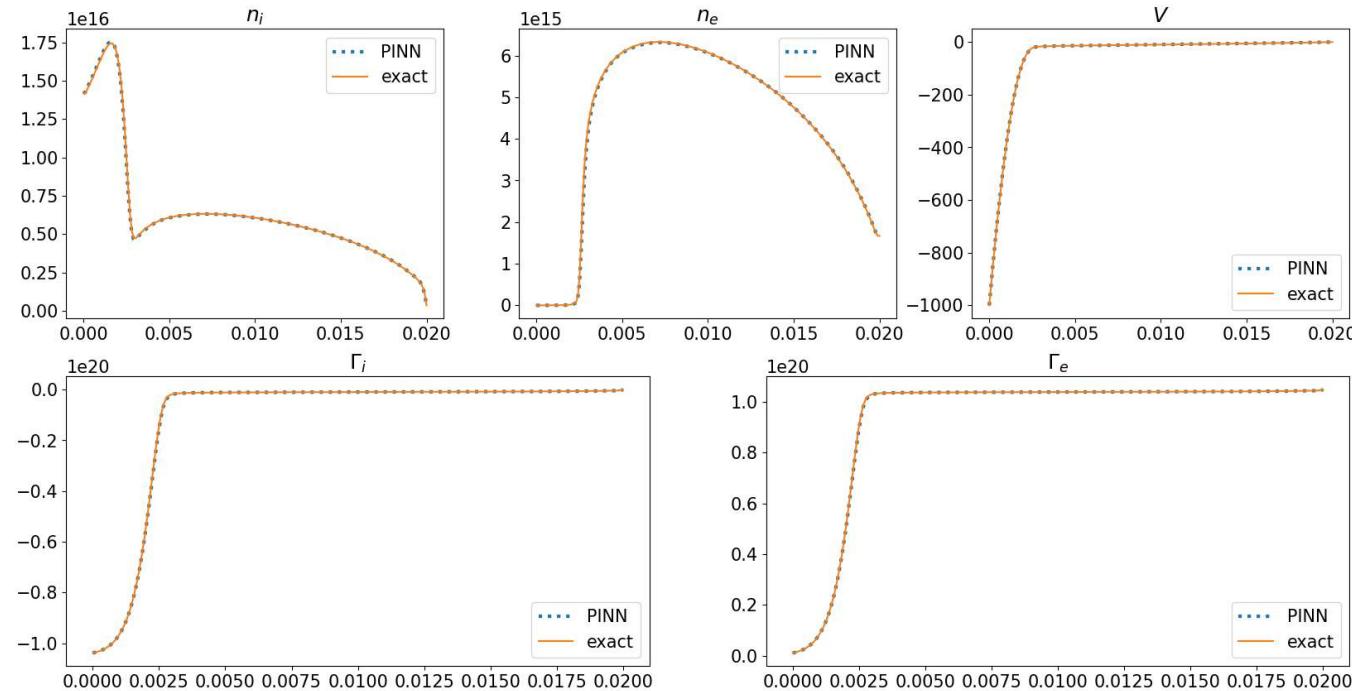
Predict results about each species



3. ML-aided Modeling

Physics-informed neural networks (PINNs)

- Normalization, SALB + PINNs
- 1D DC discharge problem



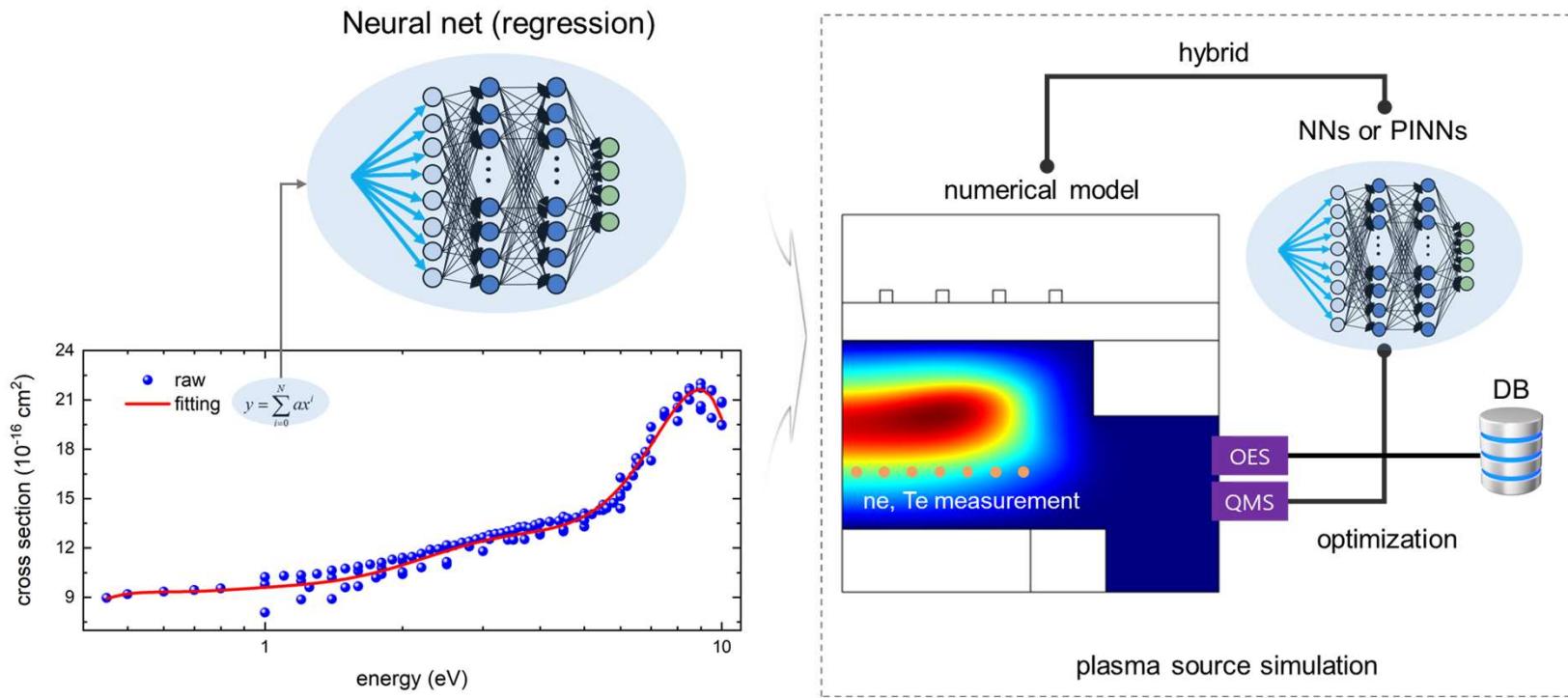
4

Summary & Future works



4. Summary & Future works

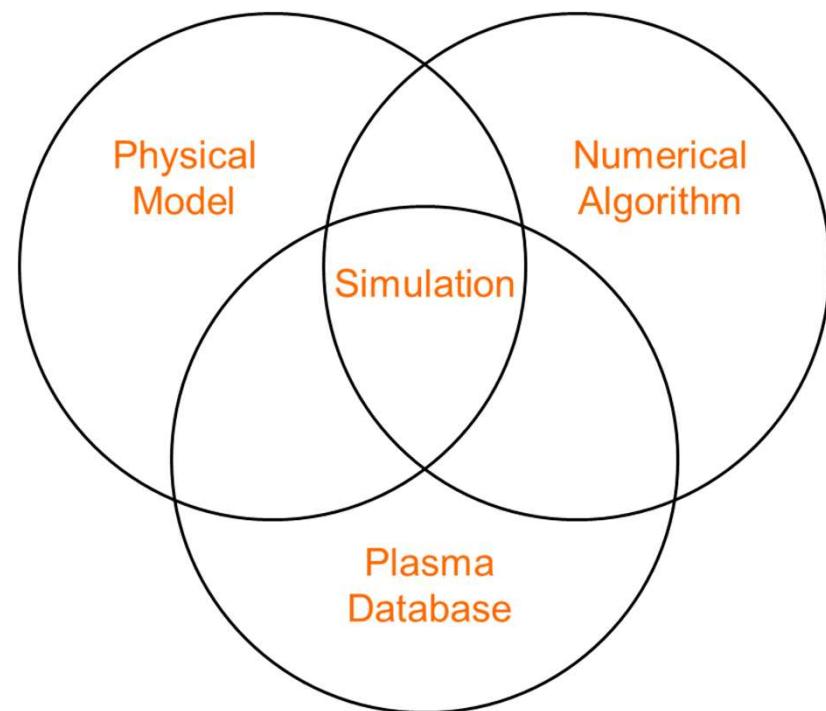
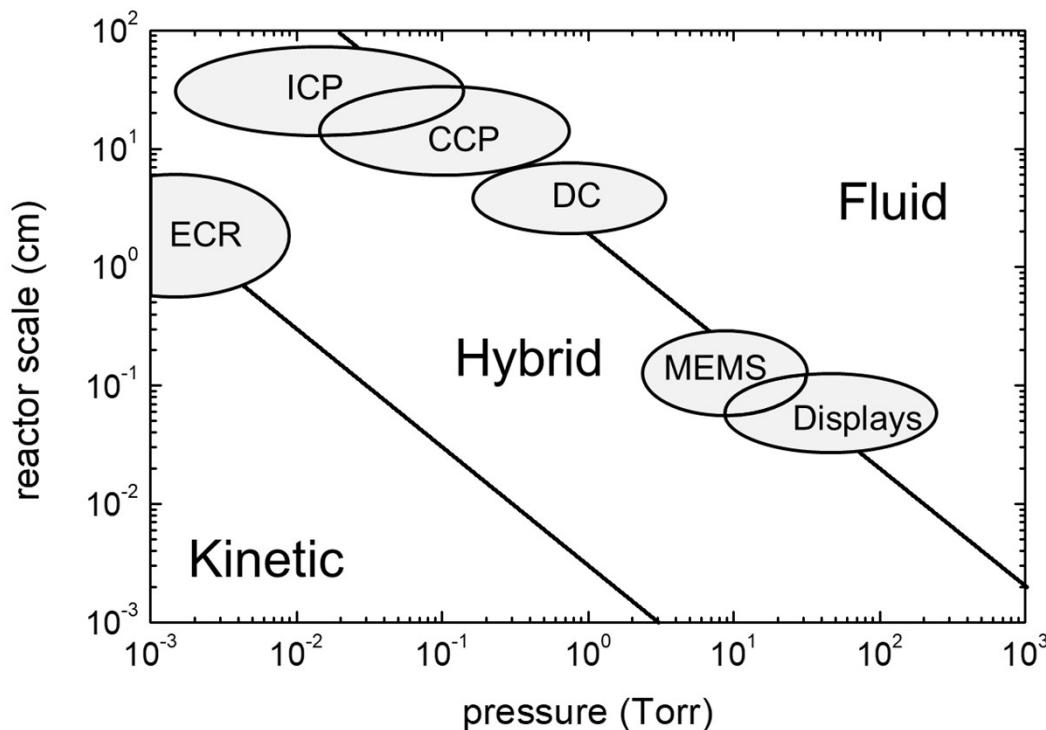
- This talk introduces our group's simulator and database development status and the results of applying machine learning technology to plasma source monitoring and simulations
- Get helps from NNs when prediction and optimization are needed
- Fill in the blank with NNs



Thank you for your attention

5. Supplementary

Kinetic, Hybrid, and Fluid models

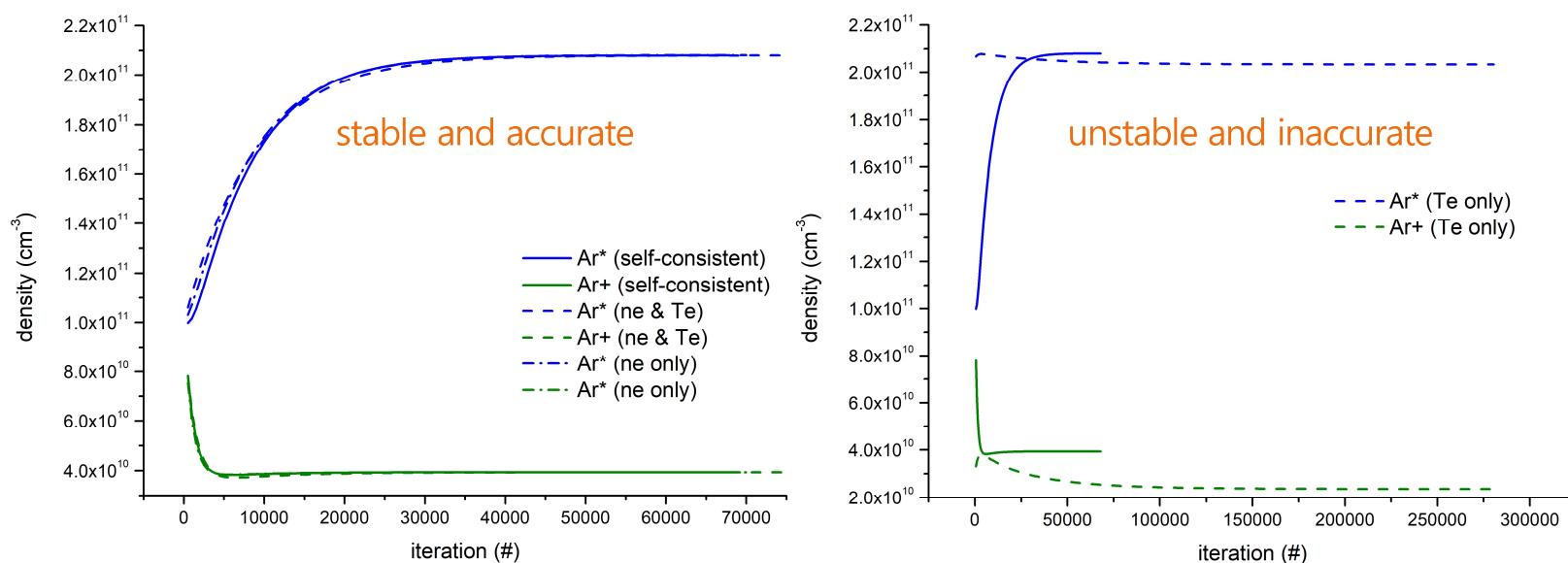


5. Supplementary

CHEM-global (chemical reaction analyzer using a global model)

Quasi-neutrality

In some cases, the quasi-neutrality condition was not satisfied → after solving the continuity equation, densities are normalized



normalization

$$\sum_i n_i^+ = \sum_j n_j^- + n_e$$
$$\rightarrow \sum_i n_i^+ - \sum_j n_j^- = n_e$$

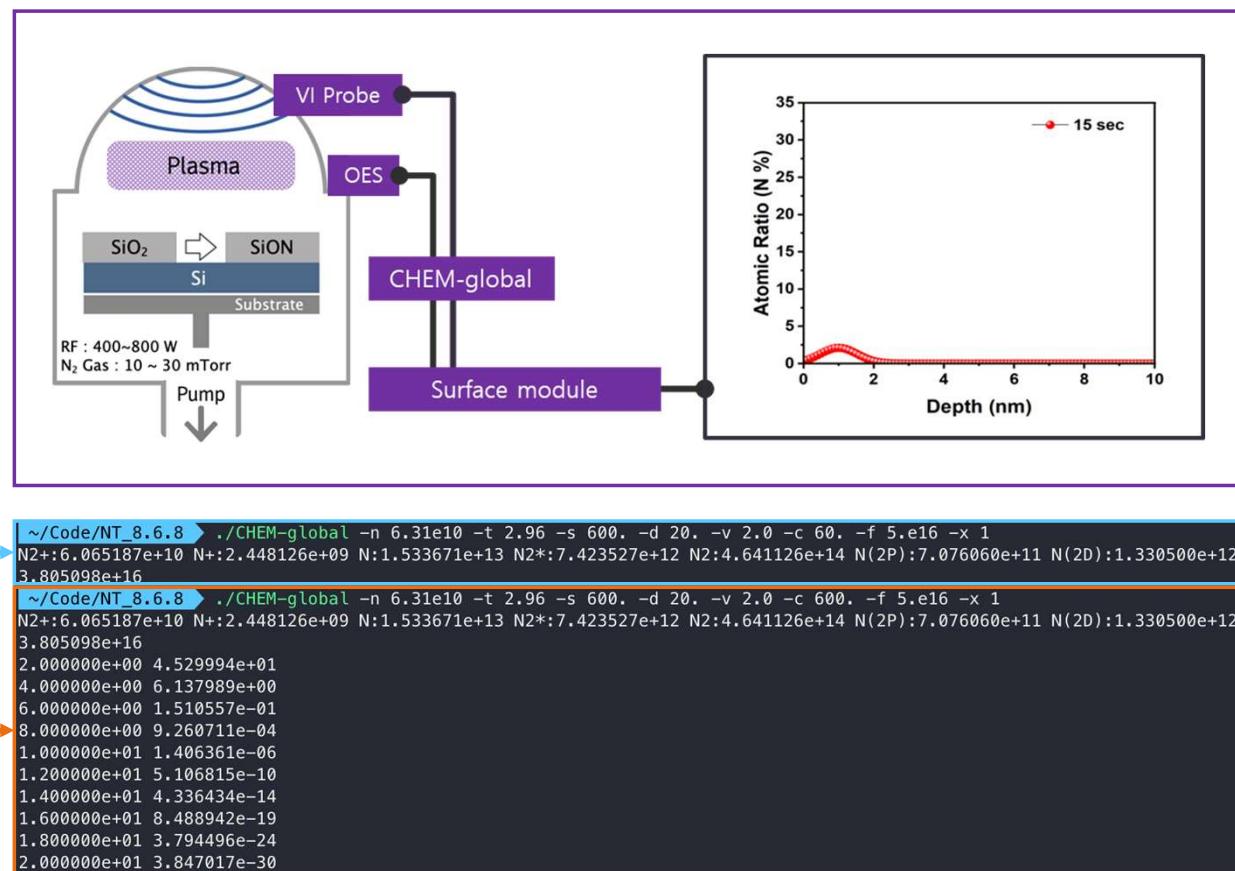
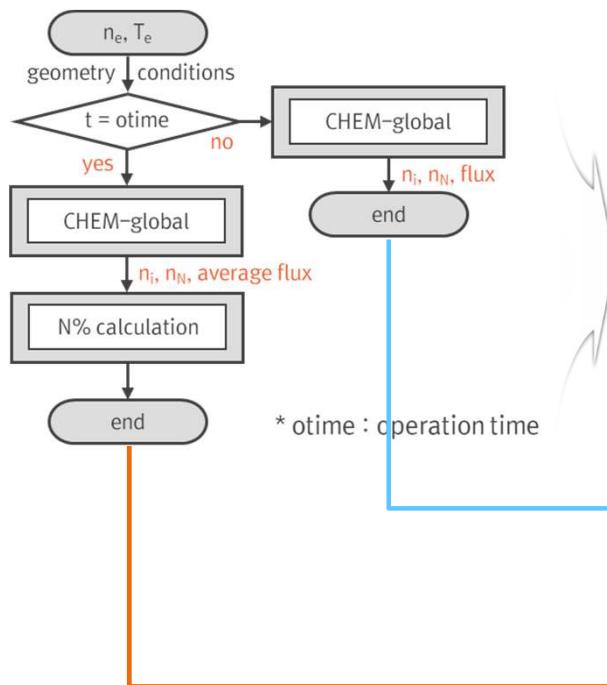
$$\text{Step 1. } \hat{n} = \sum_i n_i^+ - \sum_i n_i^-$$

$$\text{Step 2. } \kappa = \frac{n_e}{\hat{n}}$$

$$\text{Step 3. } n_i = \kappa n_i$$

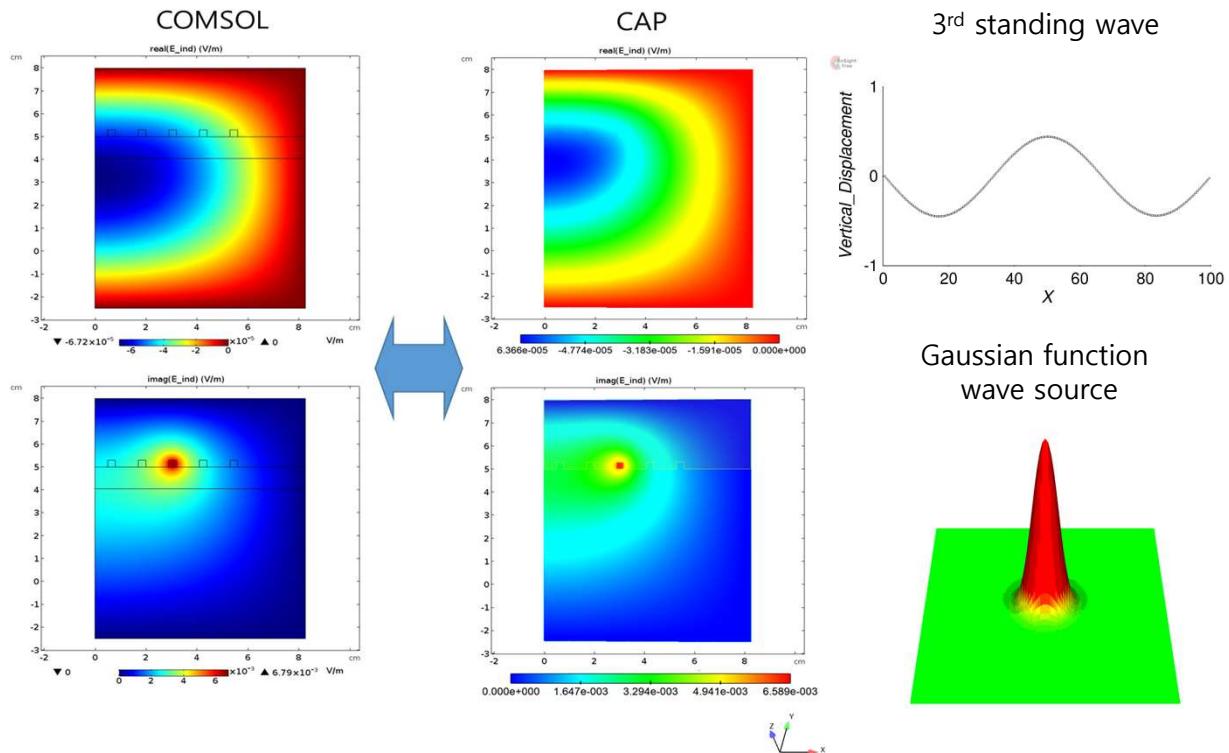
5. Supplementary

Sensor-bulk-surface coupling model



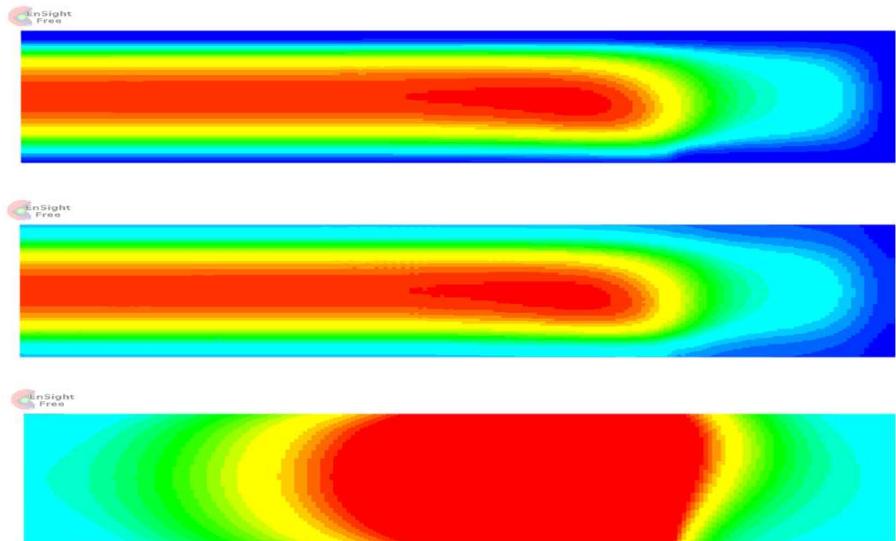
5. Supplementary

K-PLASMA unit test 1



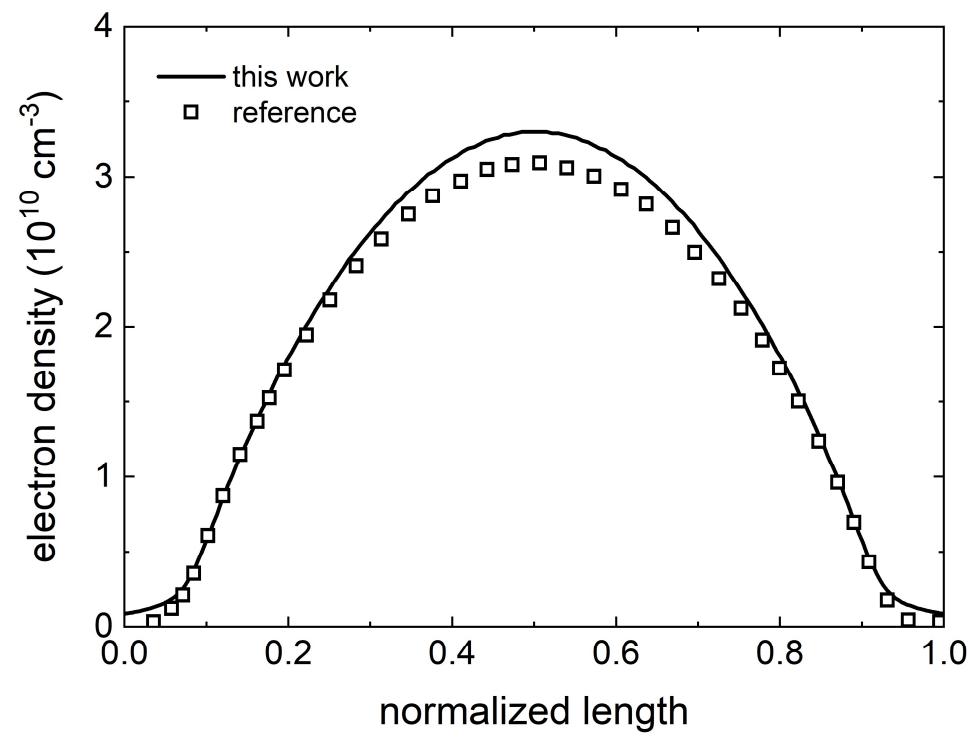
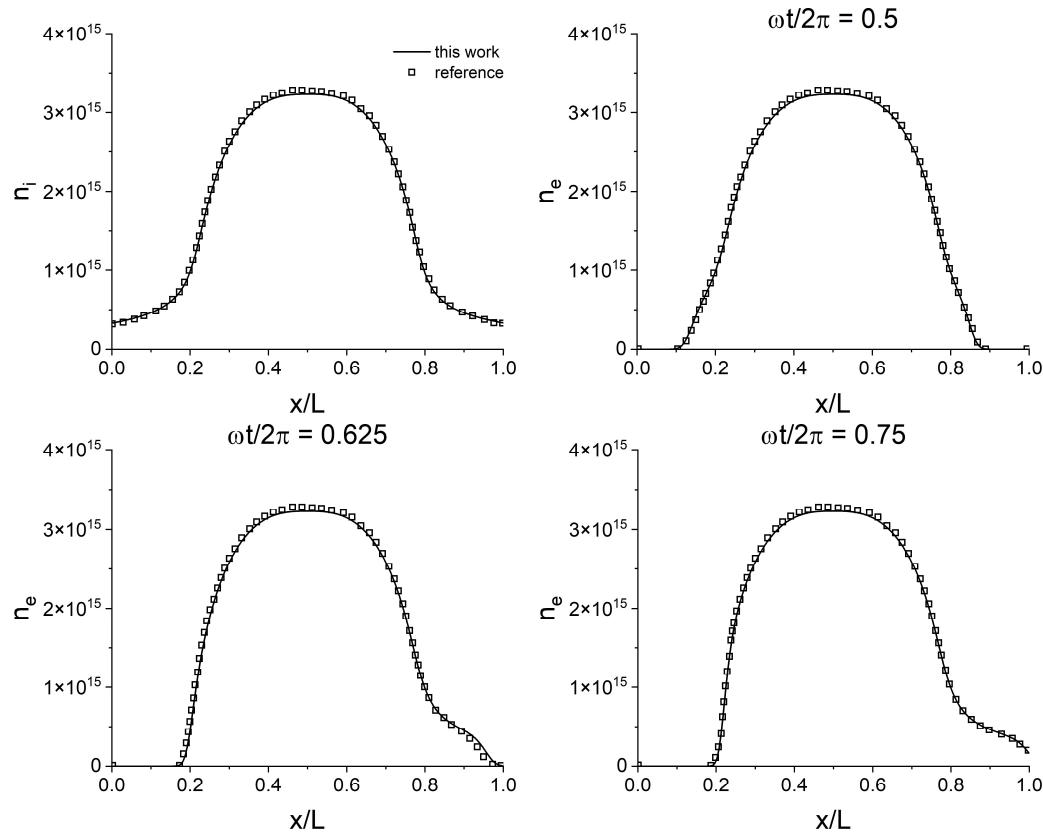
$$\text{vortex extric field } \mathbf{E}_t = -\frac{\partial \mathbf{A}}{\partial t}$$

$$-\nabla^2 \left(-\frac{\partial \mathbf{A}}{\partial t} \right) = -\mu_0 \epsilon_0 \frac{\partial^2}{\partial t^2} \left(-\frac{\partial \mathbf{A}}{\partial t} \right) - \frac{\partial}{\partial t} \left\{ \mu_0 \left[\mathbf{J} + \epsilon_0 \frac{\partial}{\partial t} (-\nabla \phi) \right] \right\}$$



5. Supplementary

K-PLASMA unit test 2



5. Supplementary

K-PLASMA – algorithm

$$\frac{\partial n_e}{\partial t} + \nabla \cdot \boldsymbol{\Gamma}_e = R_e$$

$$\frac{\partial}{\partial t} \left(\frac{3}{2} n_e k_B T_e \right) + \nabla \cdot \mathbf{Q}_e = P_{ind} - e \mathbf{E} \cdot \boldsymbol{\Gamma}_e + E_e$$

$$N_e = \ln n_e$$

$$n_\varepsilon = \frac{3}{2} n_e k_B T_e$$

$$E_n = \ln n_\varepsilon$$

$$\frac{\partial n_e}{\partial t} = \frac{n_e}{n_e} \frac{\partial n_e}{\partial t} = n_e \frac{\partial (\ln n_e)}{\partial t} = n_e \frac{\partial N_e}{\partial t}$$

$$\frac{\partial}{\partial t} \left(\frac{3}{2} n_e k_B T_e \right) = \frac{\partial n_\varepsilon}{\partial t} = \frac{n_\varepsilon}{n_\varepsilon} \frac{\partial n_\varepsilon}{\partial t} = n_\varepsilon \frac{\partial (\ln n_\varepsilon)}{\partial t} = n_\varepsilon \frac{\partial E_\varepsilon}{\partial t}$$

$$\begin{aligned} \boldsymbol{\Gamma}_e &= -\frac{qn_e}{m_e v_{eN}} \mathbf{E} - \frac{n_e}{m_e v_{eN}} \nabla T_e - \frac{T_e}{m_e v_{eN}} \nabla n_e \\ &= -\mu_e n_e \mathbf{E} - n_e \nabla D_e - D_e \nabla n_e \\ \rightarrow \boldsymbol{\Gamma}_e &= -\mu_e n_e \mathbf{E} - n_e \nabla D_e - n_e D_e \nabla N_e \end{aligned}$$

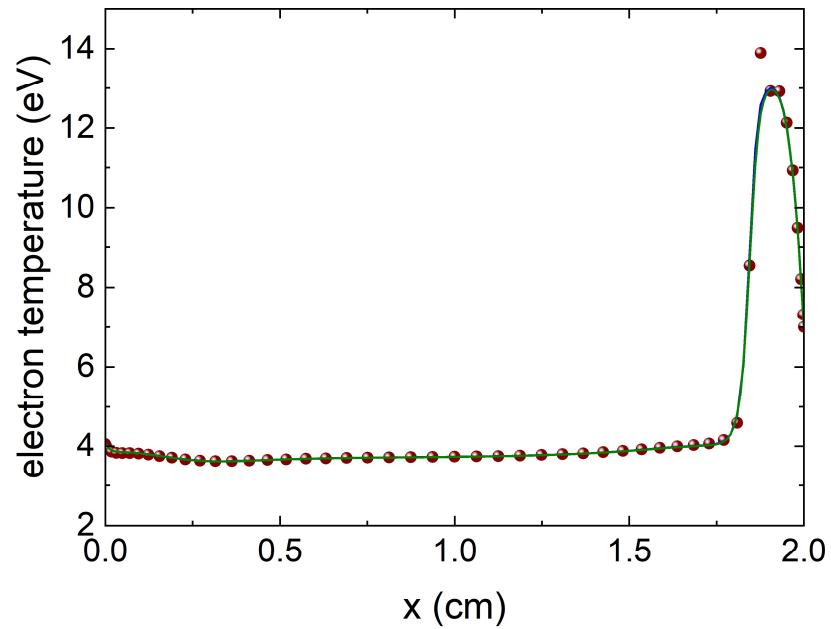
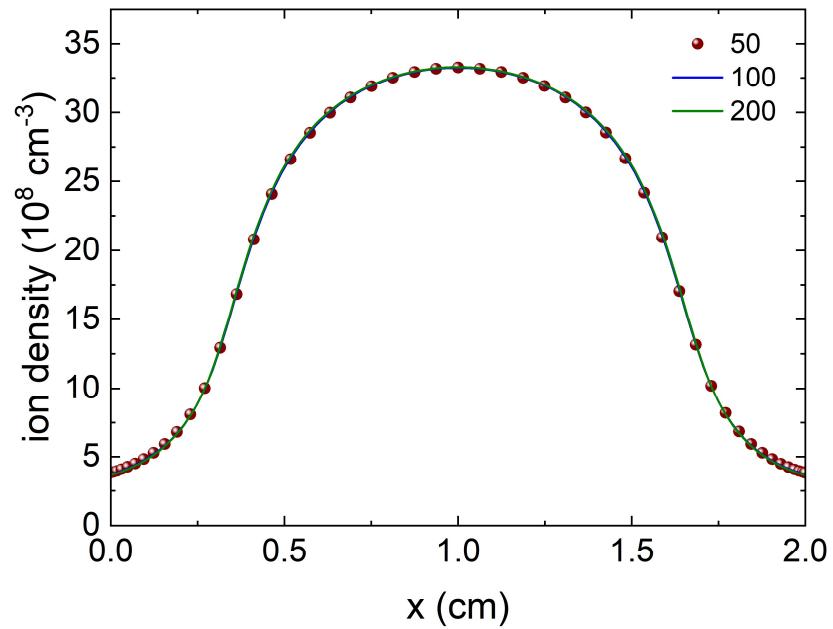
$$\Rightarrow n_e \frac{\partial N_e}{\partial t} + \nabla \cdot [-\mu_e n_e \mathbf{E} - n_e \nabla D_e - n_e D_e \nabla N_e] = R_e$$

$$\begin{aligned} \mathbf{Q}_e &= \frac{5}{2} \boldsymbol{\Gamma}_e k_B T_e - \frac{5}{2} \frac{n_e k_B T_e}{m_e v_{eN}} \nabla (k_B T_e) \\ \rightarrow \mathbf{Q}_e &= -\mu_\varepsilon \mathbf{E} n_\varepsilon - D_\varepsilon n_\varepsilon \nabla E_\varepsilon - n_\varepsilon \nabla D_\varepsilon \end{aligned}$$

$$\Rightarrow n_\varepsilon \frac{\partial E_\varepsilon}{\partial t} + \nabla \cdot [-\mu_\varepsilon n_\varepsilon \mathbf{E} - n_\varepsilon D_\varepsilon \nabla E_\varepsilon - n_\varepsilon \nabla D_\varepsilon] = P_{ind} - e \mathbf{E} \cdot \boldsymbol{\Gamma}_e + E_e$$

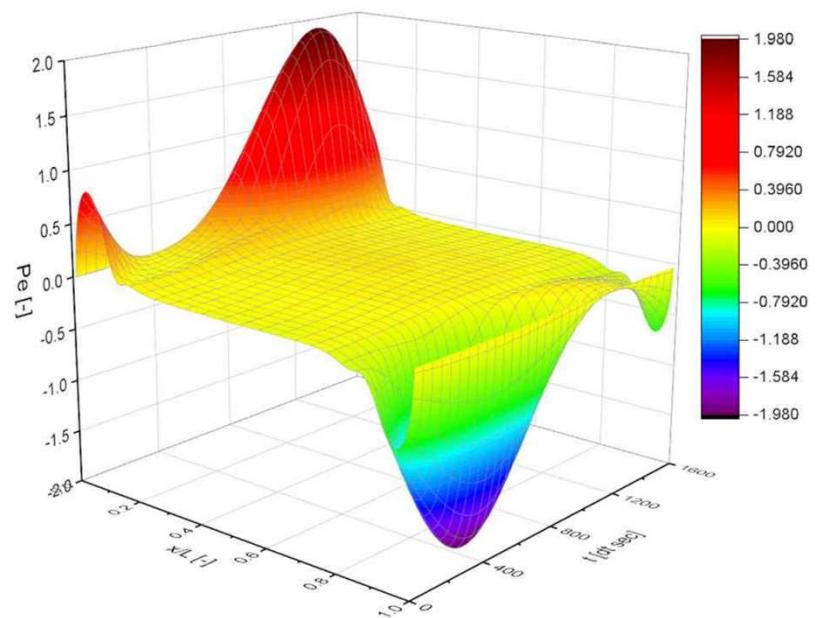
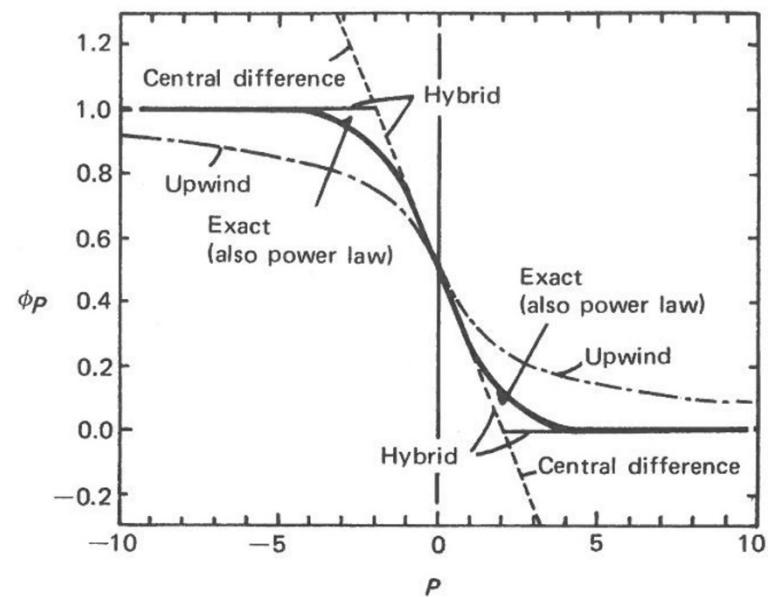
5. Supplementary

K-PLASMA – algorithm



5. Supplementary

K-PLASMA – algorithm



5. Supplementary

K-PLASMA – algorithm

$$\begin{cases} \frac{\partial \boldsymbol{\Gamma}_i}{\partial t} + \nabla \cdot (\boldsymbol{\Gamma}_i \mathbf{u}_i) = \frac{en_i}{m_i} \mathbf{E} - \frac{1}{m_i} \nabla (n_i k_B T_i) - \nu_{iN} \boldsymbol{\Gamma}_i \\ \boldsymbol{\Gamma}_i = \frac{en_i}{\nu_{iN} m_i} \mathbf{E}_{eff} - \frac{1}{\nu_{iN} m_i} \nabla (n_i k_B T_i) \end{cases}$$

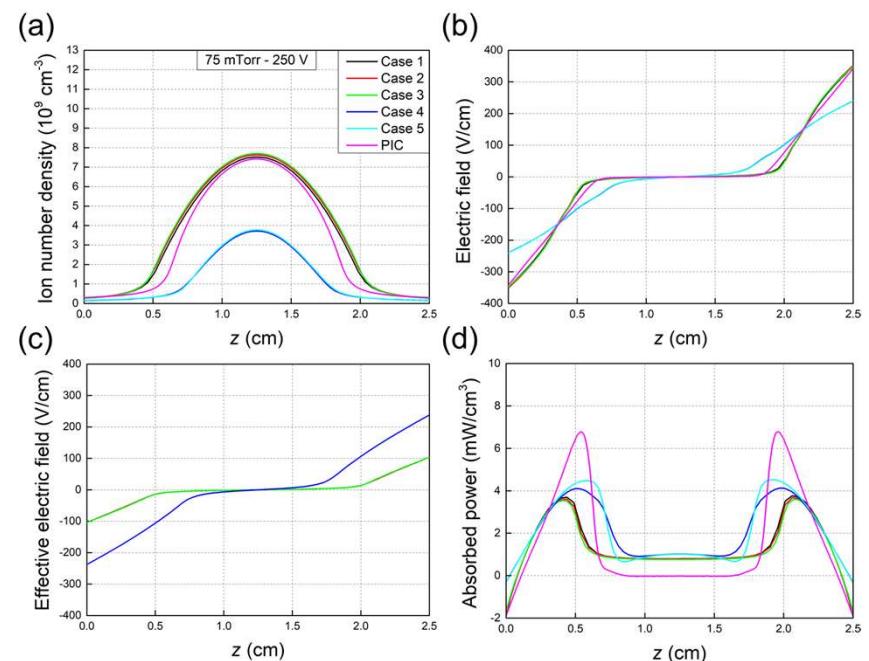
assuming $\frac{\partial}{\partial t} \left[\frac{1}{\nu_{iN} m_i} \nabla (n_i k_B T_i) \right] \approx 0, \nu_{iN} = const$

$$\frac{\partial}{\partial t} \left(\frac{en_i}{\nu_{iN} m_i} \mathbf{E}_{eff} \right) = \frac{e}{\nu_{iN} m_i} \left(n_i \frac{\partial \mathbf{E}_{eff}}{\partial t} + \mathbf{E}_{eff} \frac{\partial n_i}{\partial t} \right) = \frac{e}{\nu_{iN} m_i} \left[n_i \frac{\partial \mathbf{E}_{eff}}{\partial t} + \mathbf{E}_{eff} (R_i - \nabla \cdot \boldsymbol{\Gamma}_i) \right]$$

$$\begin{aligned} \rightarrow \frac{en_i}{\nu_{iN} m_i} \frac{\partial \mathbf{E}_{eff}}{\partial t} &= -\nabla \cdot (\boldsymbol{\Gamma}_i \mathbf{u}_i) + \frac{en_i}{m_i} \mathbf{E} - \frac{1}{m_i} \nabla (n_i k_B T_i) - \nu_{iN} \left[\frac{en_i}{\nu_{iN} m_i} \mathbf{E}_{eff} - \frac{1}{\nu_{iN} m_i} \nabla (n_i k_B T_i) \right] - \frac{e}{\nu_{iN} m_i} \mathbf{E}_{eff} (R_i - \nabla \cdot \boldsymbol{\Gamma}_i) \\ &= -\nabla \cdot (\boldsymbol{\Gamma}_i \mathbf{u}_i) + \frac{en_i}{m_i} \mathbf{E} - \frac{1}{m_i} \nabla (n_i k_B T_i) - \frac{en_i}{m_i} \mathbf{E}_{eff} + \frac{1}{m_i} \nabla (n_i k_B T_i) - \frac{e}{\nu_{iN} m_i} \mathbf{E}_{eff} (R_i - \nabla \cdot \boldsymbol{\Gamma}_i) \end{aligned}$$

$$\rightarrow \frac{\partial \mathbf{E}_{eff}}{\partial t} = -\frac{\nu_{iN} m_i}{en_i} \nabla \cdot (\boldsymbol{\Gamma}_i \mathbf{u}_i) + \nu_{iN} \mathbf{E} - \nu_{iN} \mathbf{E}_{eff} - \frac{1}{n_i} \mathbf{E}_{eff} (R_i - \nabla \cdot \boldsymbol{\Gamma}_i)$$

$$\Rightarrow \frac{\partial \mathbf{E}_{eff}}{\partial t} = \nu_{iN} (\mathbf{E} - \mathbf{E}_{eff}) - \frac{\nu_{iN} m_i}{en_i} \nabla \cdot (\boldsymbol{\Gamma}_i \mathbf{u}_i) - \frac{1}{n_i} \mathbf{E}_{eff} (R_i - \nabla \cdot \boldsymbol{\Gamma}_i)$$



Case 1; full momentum equation

Case 2; full effective electric field

Case 3; Ignoring the third term on RHS

Case 4; Ignoring the second and third terms on RHS

Case 5; without the effective electric field

5. Supplementary

Equivalent circuit of dielectric wall ICP sources

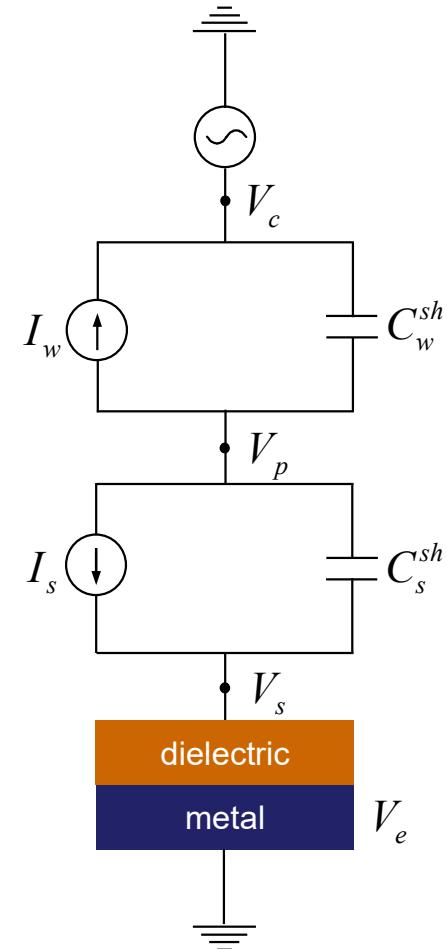
$$\begin{cases} C_w^{sh} \frac{\partial}{\partial t} (V_p - V_c) + I_w + C_s^{sh} \frac{\partial}{\partial t} (V_p - V_s) + I_s = 0 \\ \frac{\partial V_s}{\partial t} = \frac{1}{C_{eff}} (I_i - I_e + I_d) = \frac{1}{C_{eff}} I_s + \frac{1}{C_{eff}} C_s^{sh} \frac{\partial}{\partial t} (V_p - V_s) \end{cases}$$

$I_s = I_i - I_e \quad I_d = C_s^{sh} \frac{\partial}{\partial t} (V_p - V_s)$

$$\Rightarrow \begin{cases} C_w^{sh} \frac{\partial}{\partial t} (V_p - V_c) + I_w + C_s^{sh} \frac{\partial}{\partial t} (V_p - V_s) + I_s = 0 \\ \frac{\partial V_s}{\partial t} = \frac{1}{C_{eff}} I_s + \frac{C_s^{sh}}{C_{eff}} \frac{\partial}{\partial t} (V_p - V_s) \end{cases}$$

where $C_{eff} = \frac{\epsilon_r \epsilon_0 A_w}{d_f}$, A_w is the surface area of the dielectric wall,

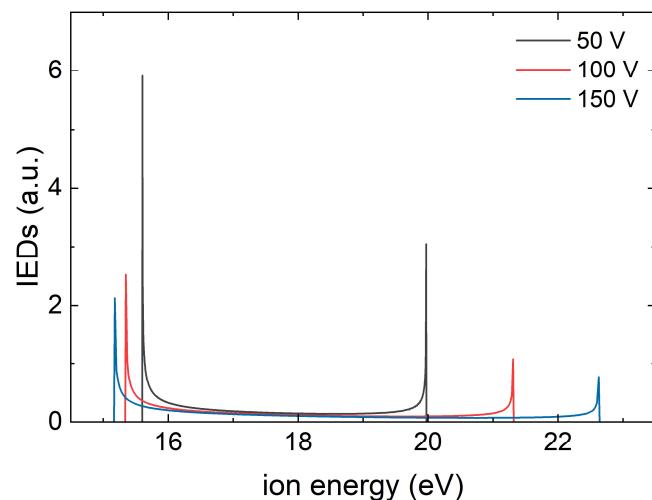
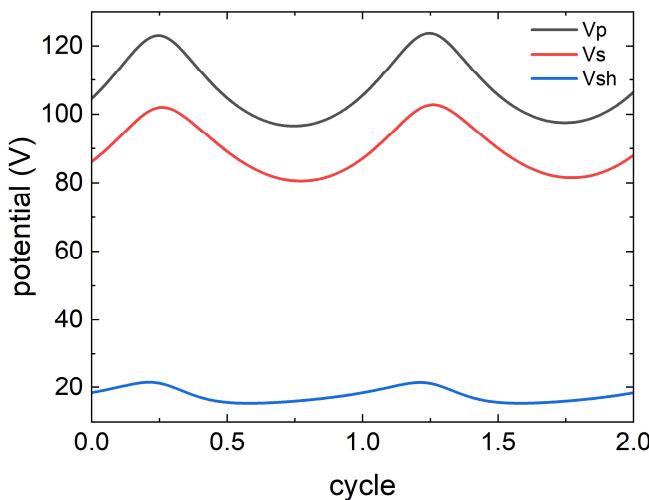
ϵ_r and d_f are the dielectric constant and thickness of the dielectric material.



5. Supplementary

Equivalent circuit of dielectric wall ICP sources

$$\begin{cases} \frac{\partial V_p}{\partial t} = \frac{C_w^{sh} C_{eff} + C_w^{sh} C_s^{sh}}{C_w^{sh} C_{eff} + C_w^{sh} C_s^{sh} + C_s^{sh} C_{eff}} \frac{\partial V_c}{\partial t} - \frac{C_{eff} + C_s^{sh}}{C_w^{sh} C_{eff} + C_w^{sh} C_s^{sh} + C_s^{sh} C_{eff}} \left[I_w + I_s - \frac{C_s^{sh}}{C_{eff} + C_s^{sh}} I_s \right] \\ \frac{\partial V_s}{\partial t} = \frac{1}{C_{eff} + C_s^{sh}} I_s + \frac{C_s^{sh}}{C_{eff} + C_s^{sh}} \left\{ \frac{C_w^{sh} C_{eff} + C_w^{sh} C_s^{sh}}{C_w^{sh} C_{eff} + C_w^{sh} C_s^{sh} + C_s^{sh} C_{eff}} \frac{\partial V_c}{\partial t} - \frac{C_{eff} + C_s^{sh}}{C_w^{sh} C_{eff} + C_w^{sh} C_s^{sh} + C_s^{sh} C_{eff}} \left[I_w + I_s - \frac{C_s^{sh}}{C_{eff} + C_s^{sh}} I_s \right] \right\} \end{cases}$$



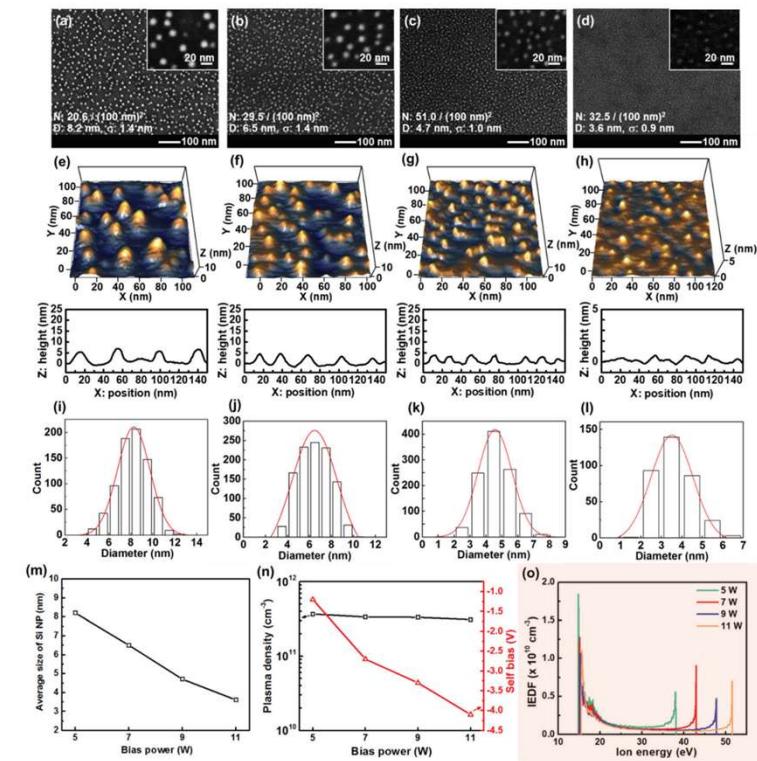
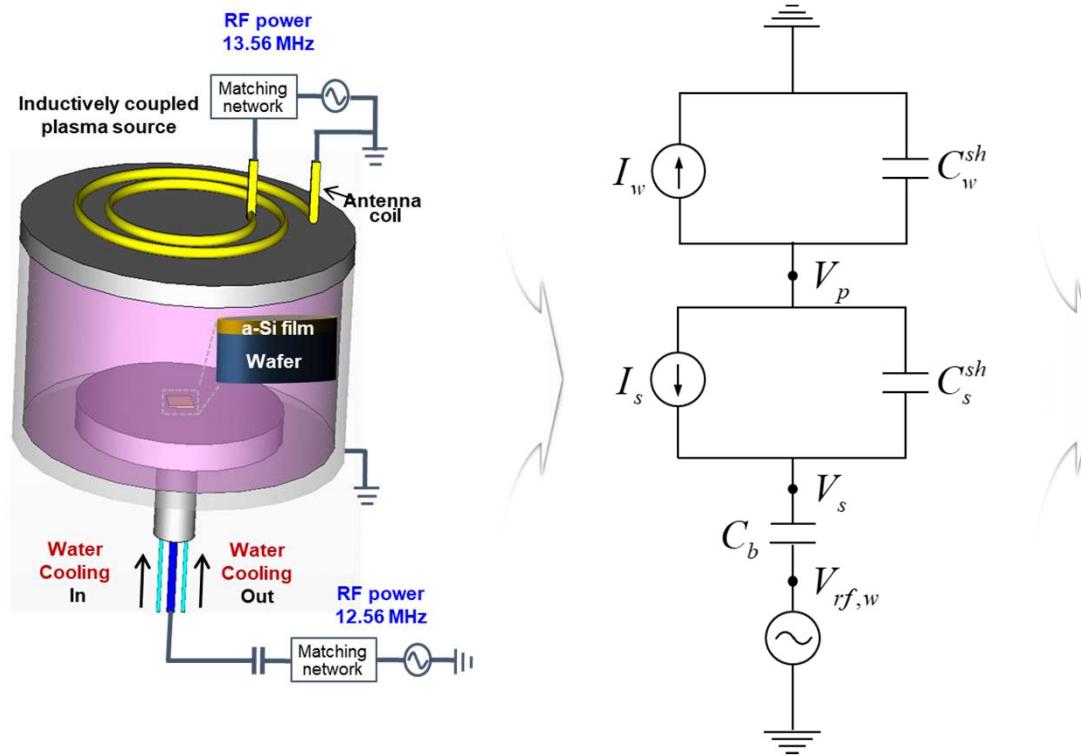
$$\frac{d\chi}{dx} \left(\frac{\partial f}{\partial \chi} + \frac{\partial f}{\partial y} \right) = -q(y) f(\chi, y) + C(\chi) \delta(y)$$

where $\chi = \frac{-e\phi}{k_B T_i}$, $x = \frac{z}{L}$, $y = \frac{m_i v^2}{2k_B T_i}$, $q(y) = \frac{L}{\lambda(y)}$

Riemann obtained the IEDs at the chamber wall by solving the Boltzmann equation

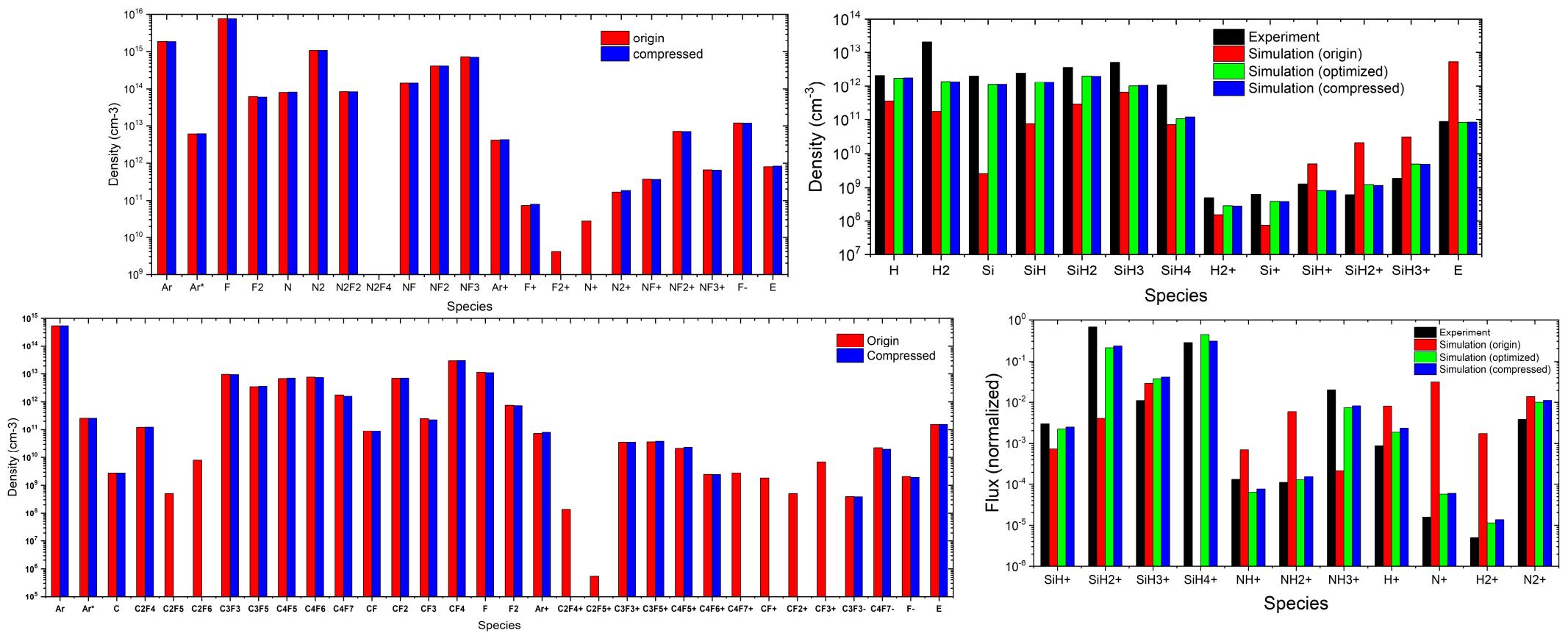
5. Supplementary

Equivalent circuit for rf-biased sheath



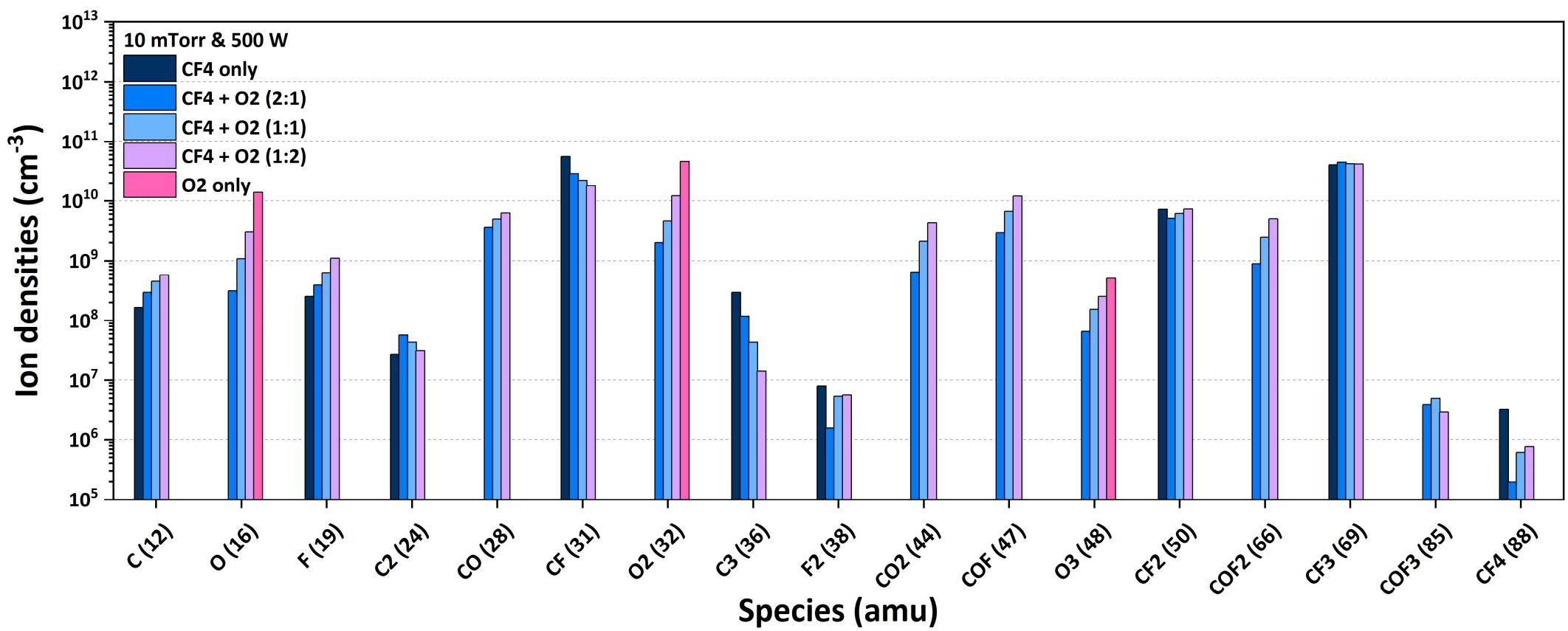
5. Supplementary

Database development



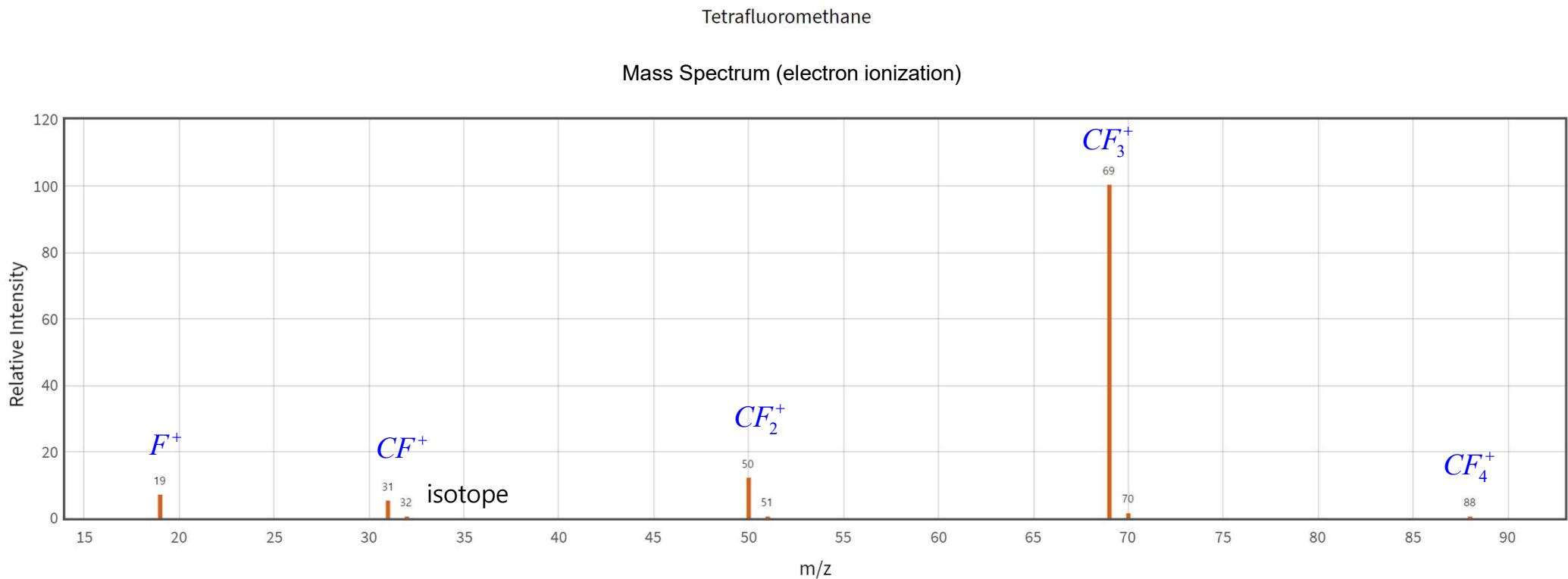
5. Supplementary

Database development (CF_4/O_2 mixture)



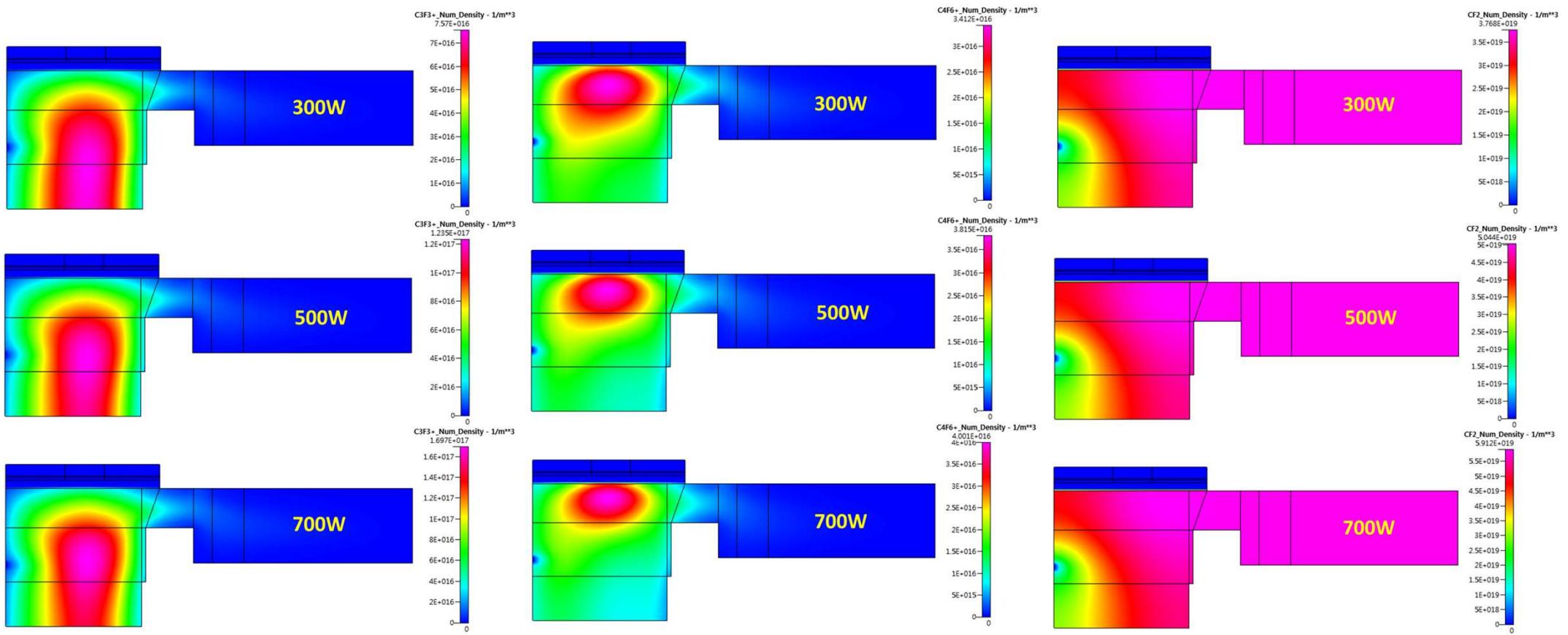
5. Supplementary

Database development (CF_4/O_2 mixture)



5. Supplementary

2D simulations at 20 mTorr



4. Summary & Future works

